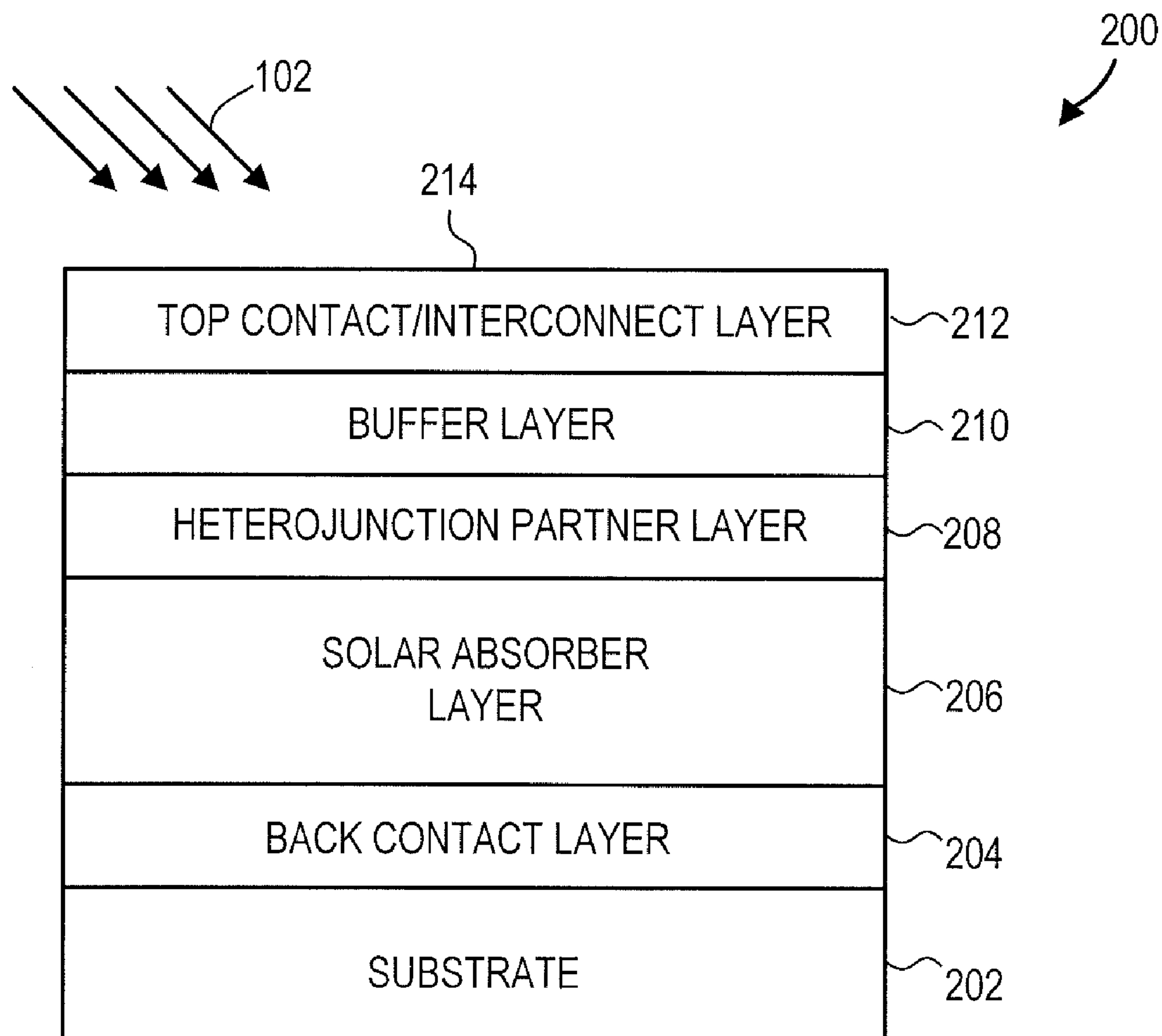


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(19) **United States**(12) **Patent Application Publication**
Woods et al.(10) **Pub. No.: US 2009/0020149 A1**(43) **Pub. Date: Jan. 22, 2009**(54) **HYBRID MULTI-JUNCTION PHOTOVOLTAIC CELLS AND ASSOCIATED METHODS****Publication Classification**(76) Inventors: **Lawrence M. Woods**, Littleton, CO (US); **Rosine M. Ribelin**, Lakewood, CO (US); **Prem Nath**, Denver, CO (US)(51) **Int. Cl.**
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B05D 5/12 (2006.01)
(52) **U.S. Cl. 136/244; 136/256; 427/97.6; 427/76**
(57) **ABSTRACT**Correspondence Address:
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BOULDER, CO 80301 (US)(21) Appl. No.: **12/174,626**(22) Filed: **Jul. 16, 2008****Related U.S. Application Data**

(60) Provisional application No. 60/950,087, filed on Jul. 16, 2007, provisional application No. 60/956,107, filed on Aug. 15, 2007, provisional application No. 61/031,652, filed on Feb. 26, 2008.

A multi-junction photovoltaic cell includes a substrate and a back contact layer formed on the substrate. A low bandgap Group IB-IIIB-VIB₂ material solar absorber layer is formed on the back contact layer. A heterojunction partner layer is formed on the low bandgap solar absorber layer, to help form the bottom cell junction, and the heterojunction partner layer includes at least one layer of a high resistivity material having a resistivity of at least 100 ohms-centimeter. The high resistivity material has the formula (Zn and/or Mg)(S, Se, O, and/or OH). A conductive interconnect layer is formed above the heterojunction partner layer, and at least one additional single-junction photovoltaic cell is formed on the conductive interconnect layer, as a top cell. The top cell may have an amorphous Silicon or p-type Cadmium Selenide solar absorber layer. Cadmium Selenide may be converted from n-type to p-type with a chloride doping process.



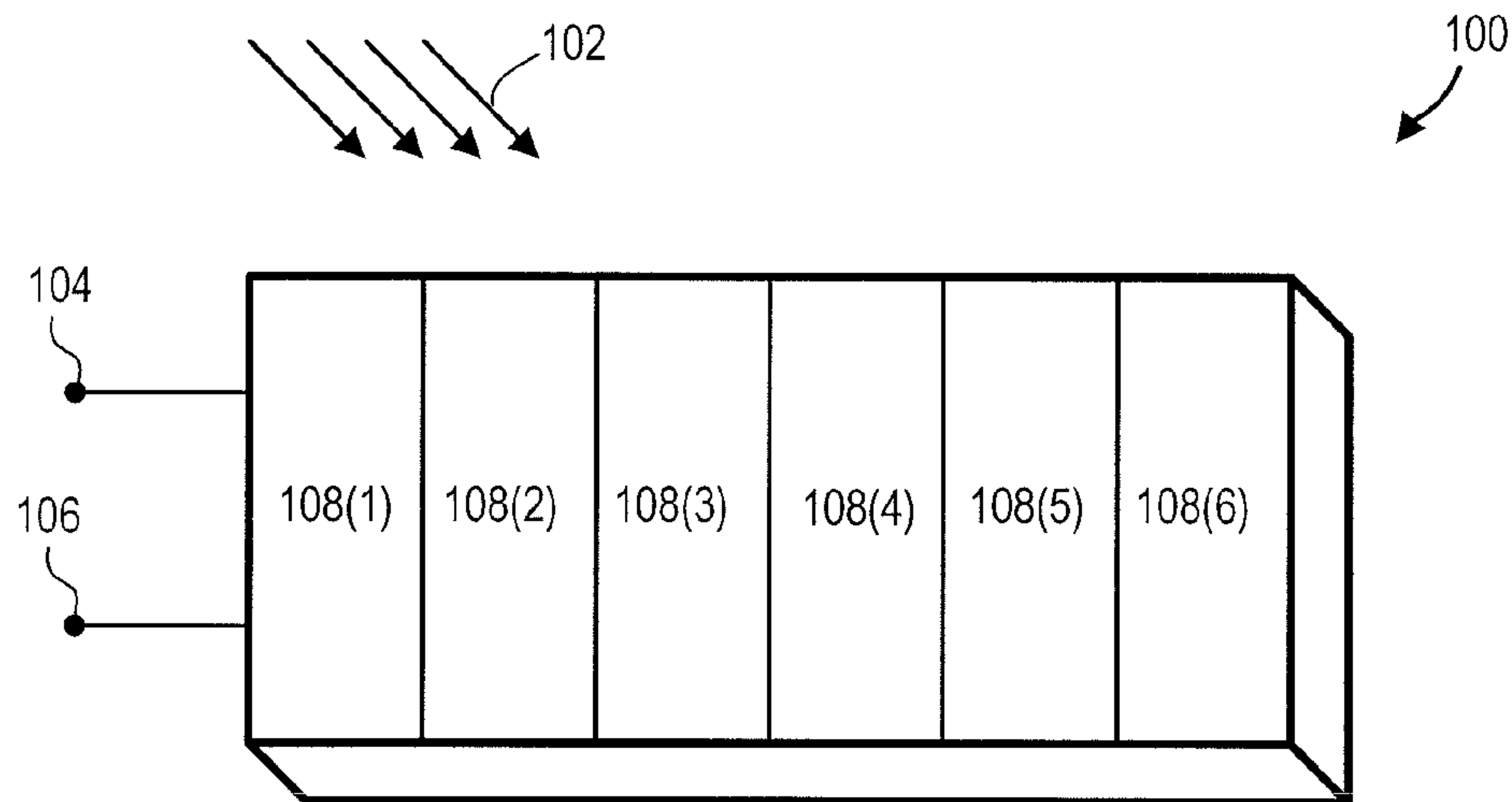


FIG. 1

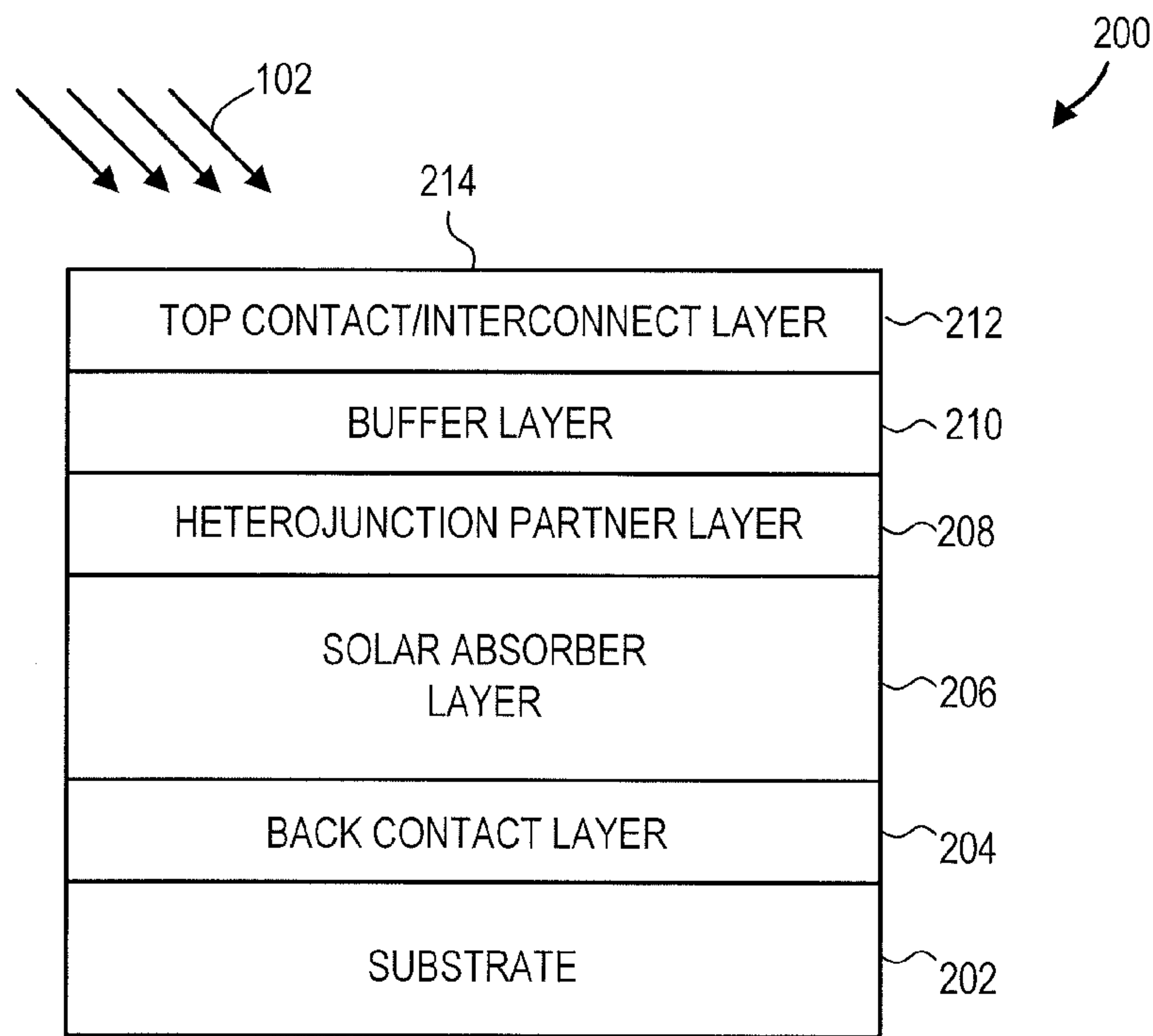


FIG. 2

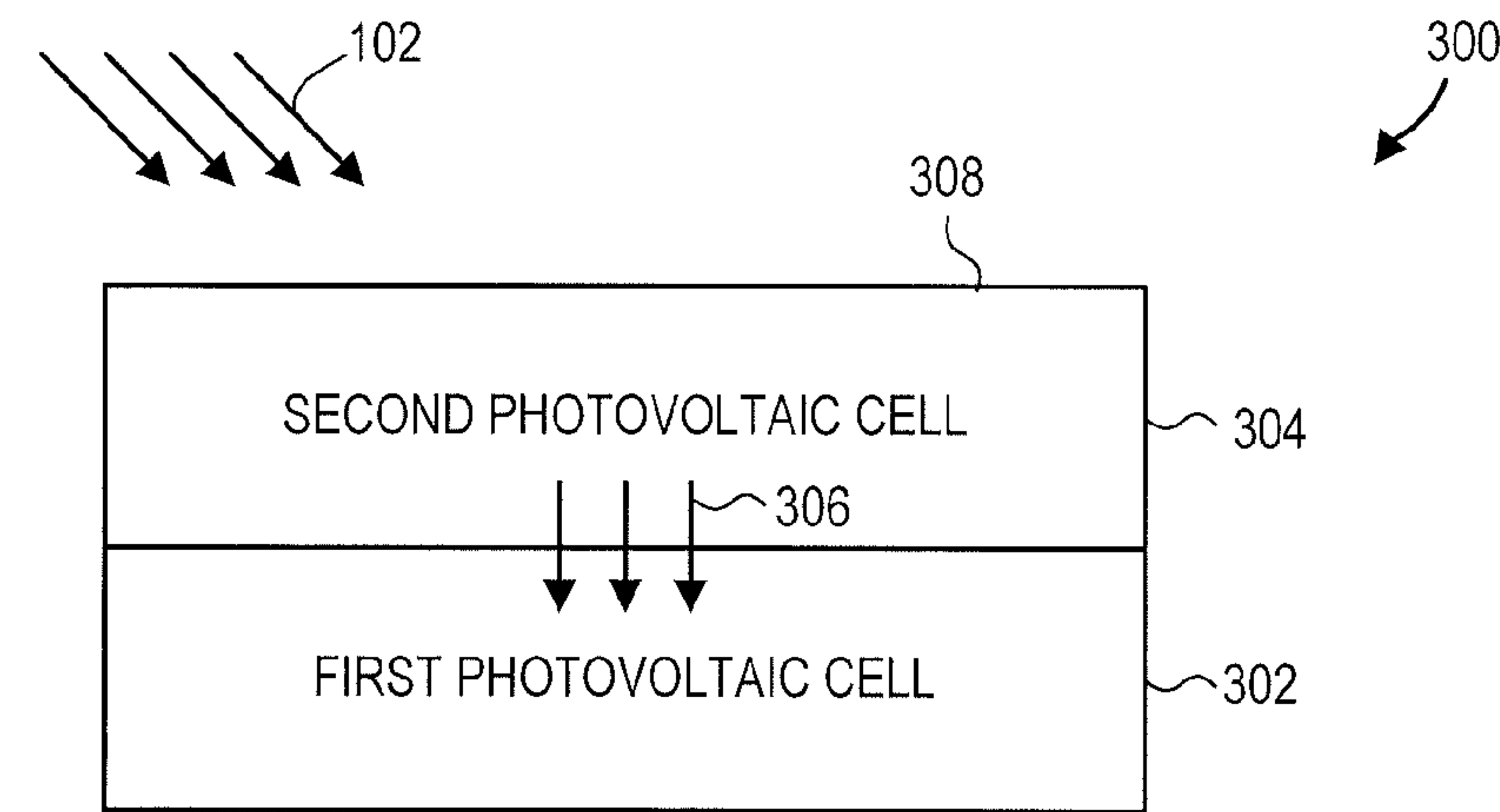


FIG. 3

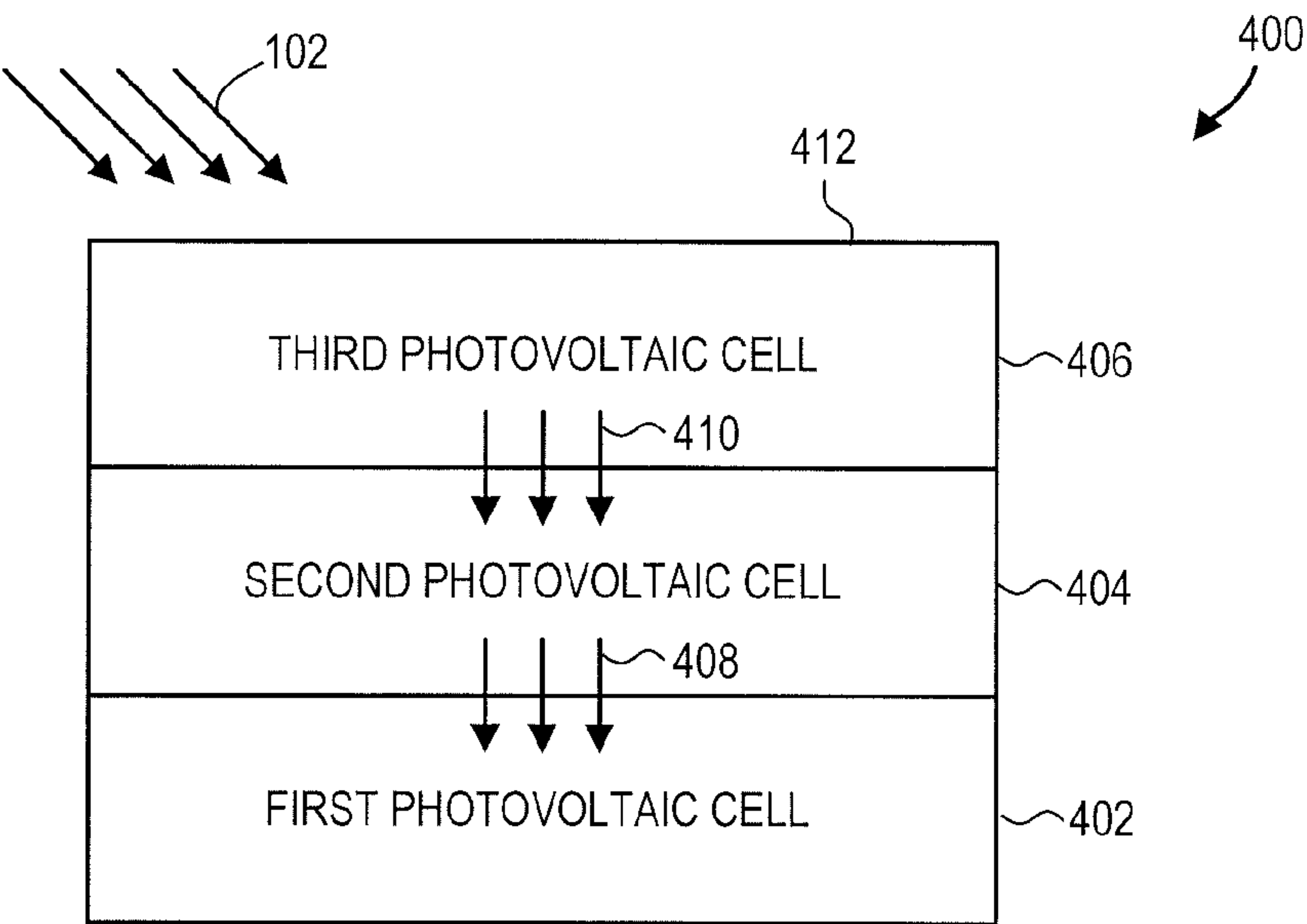


FIG. 4

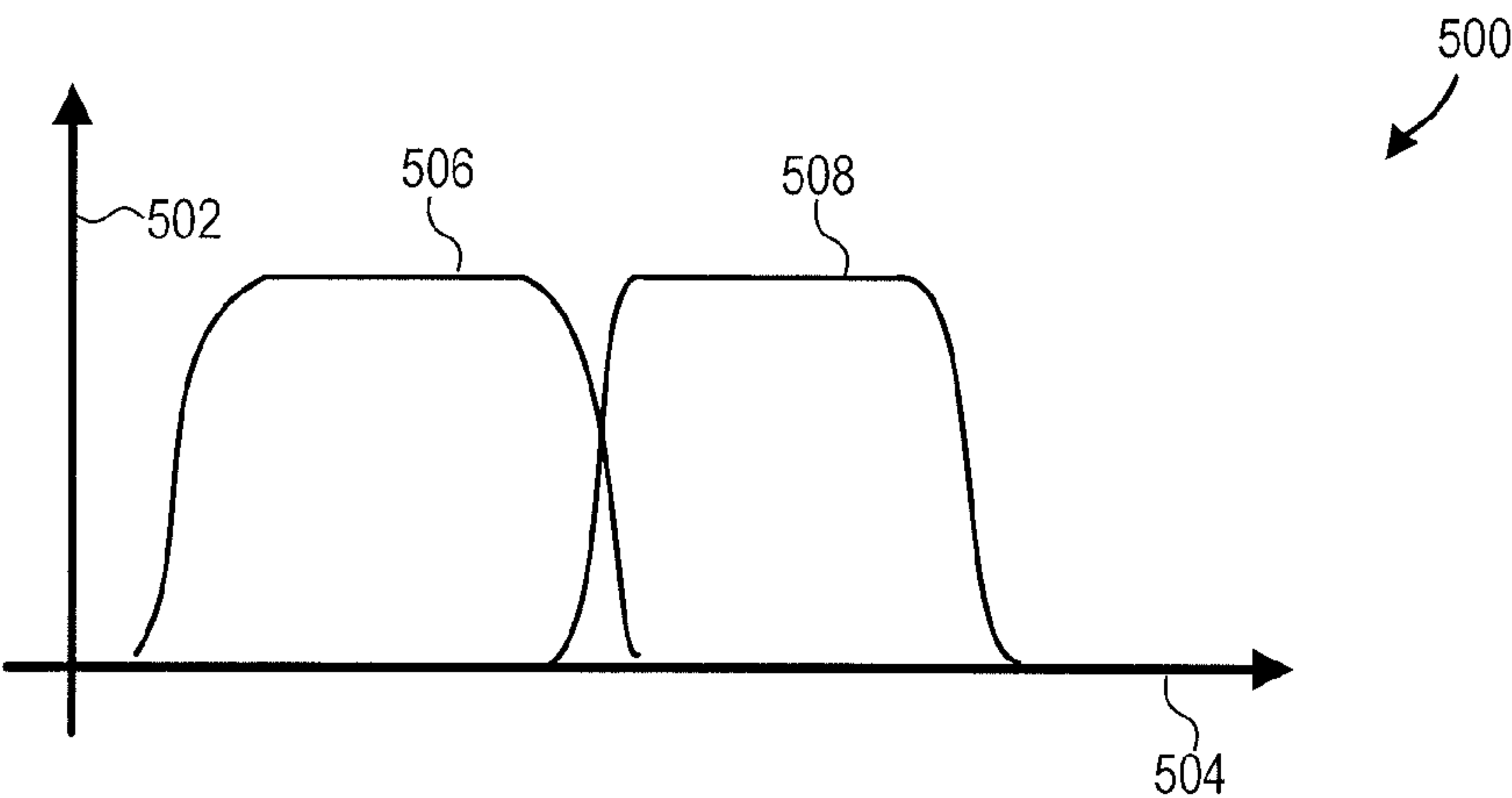


FIG. 5

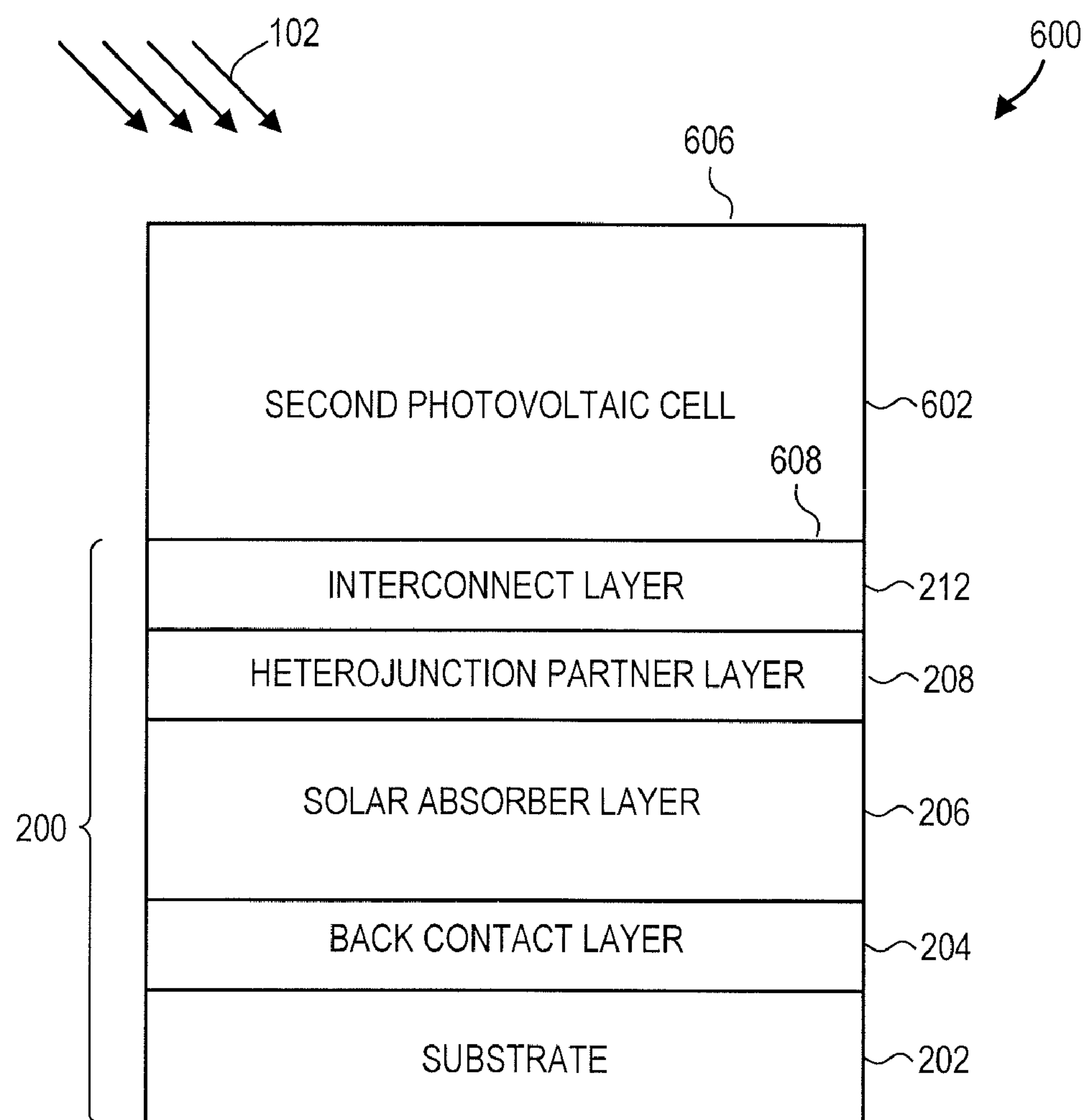


FIG. 6

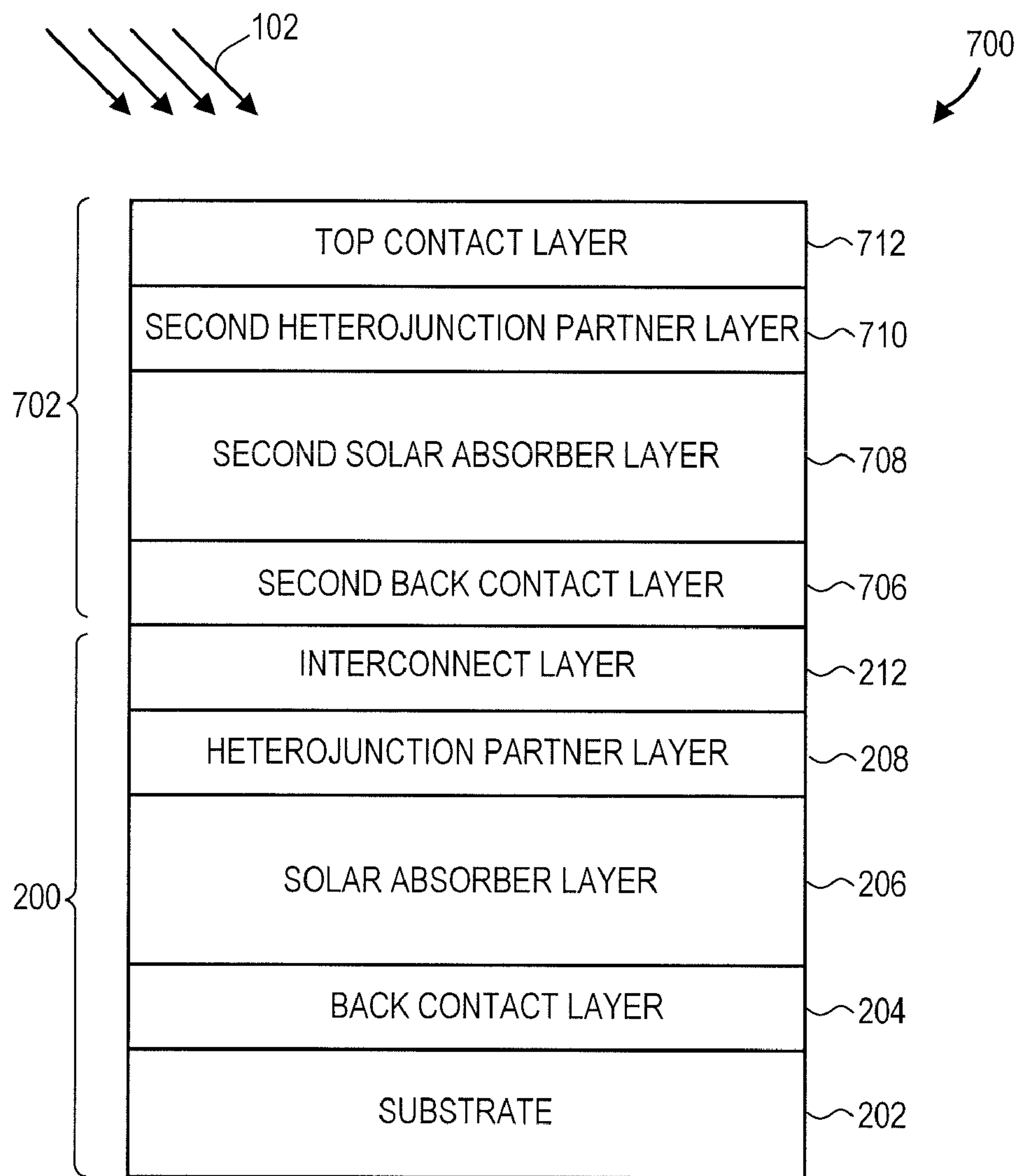


FIG. 7

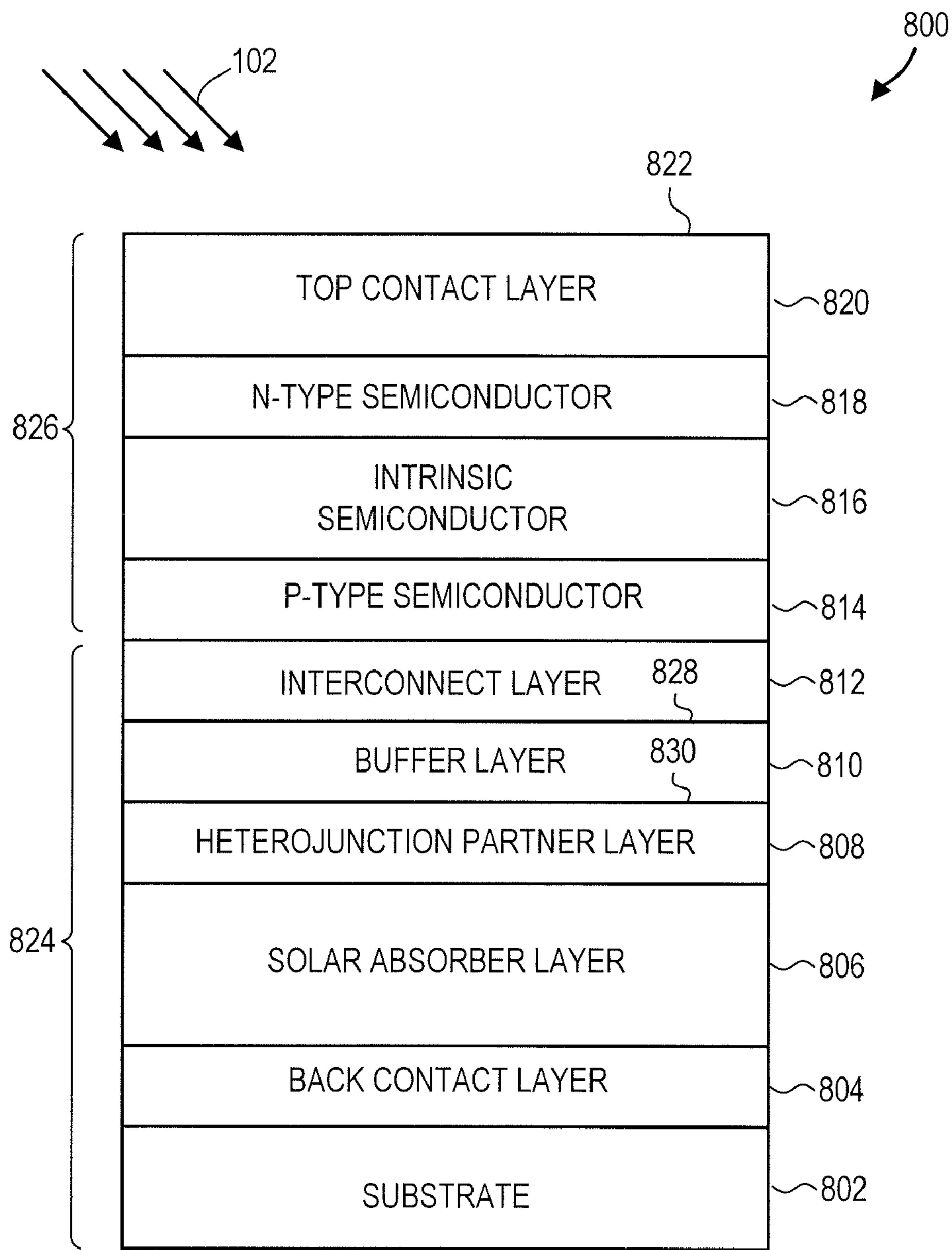


FIG. 8

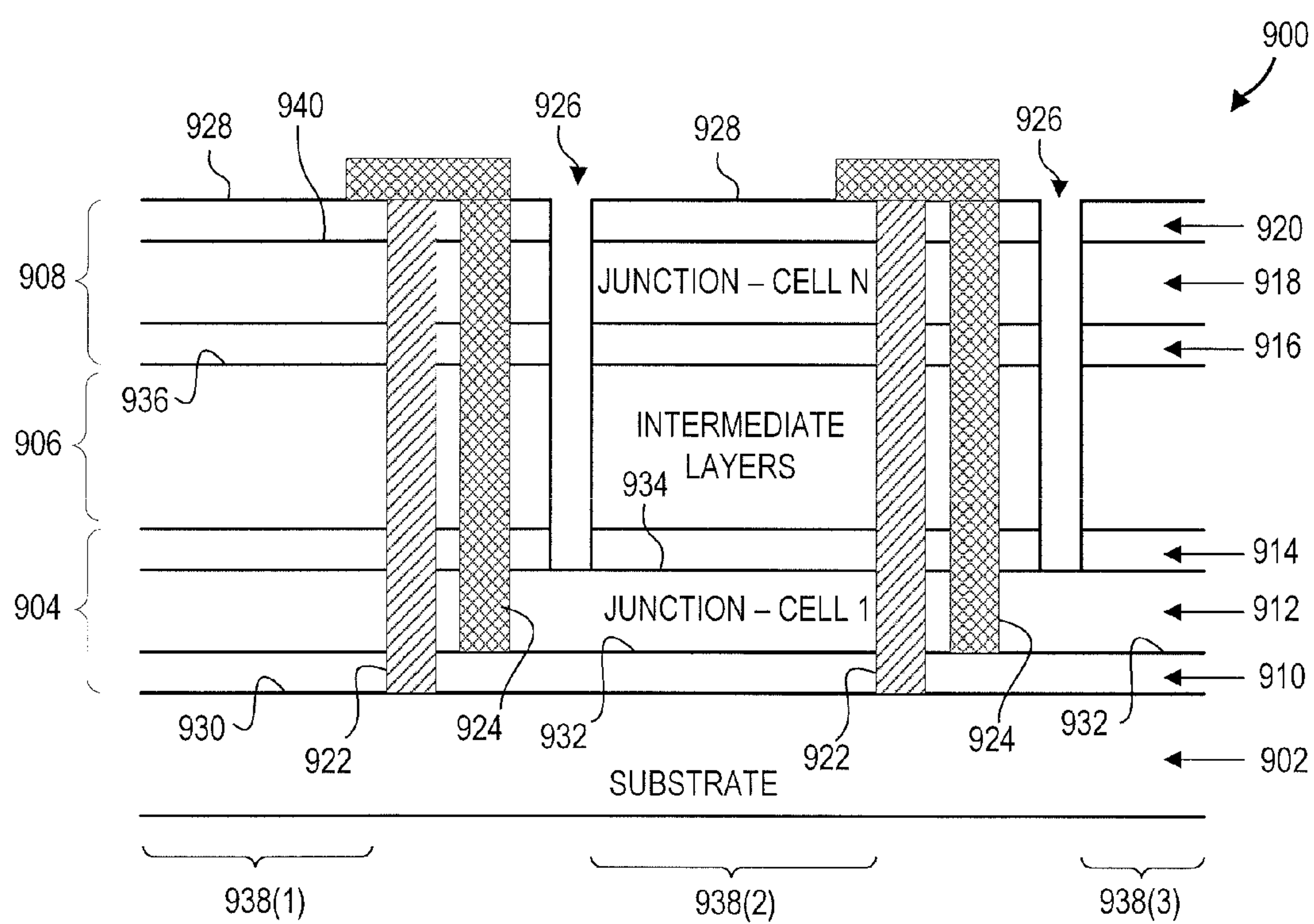


FIG. 9

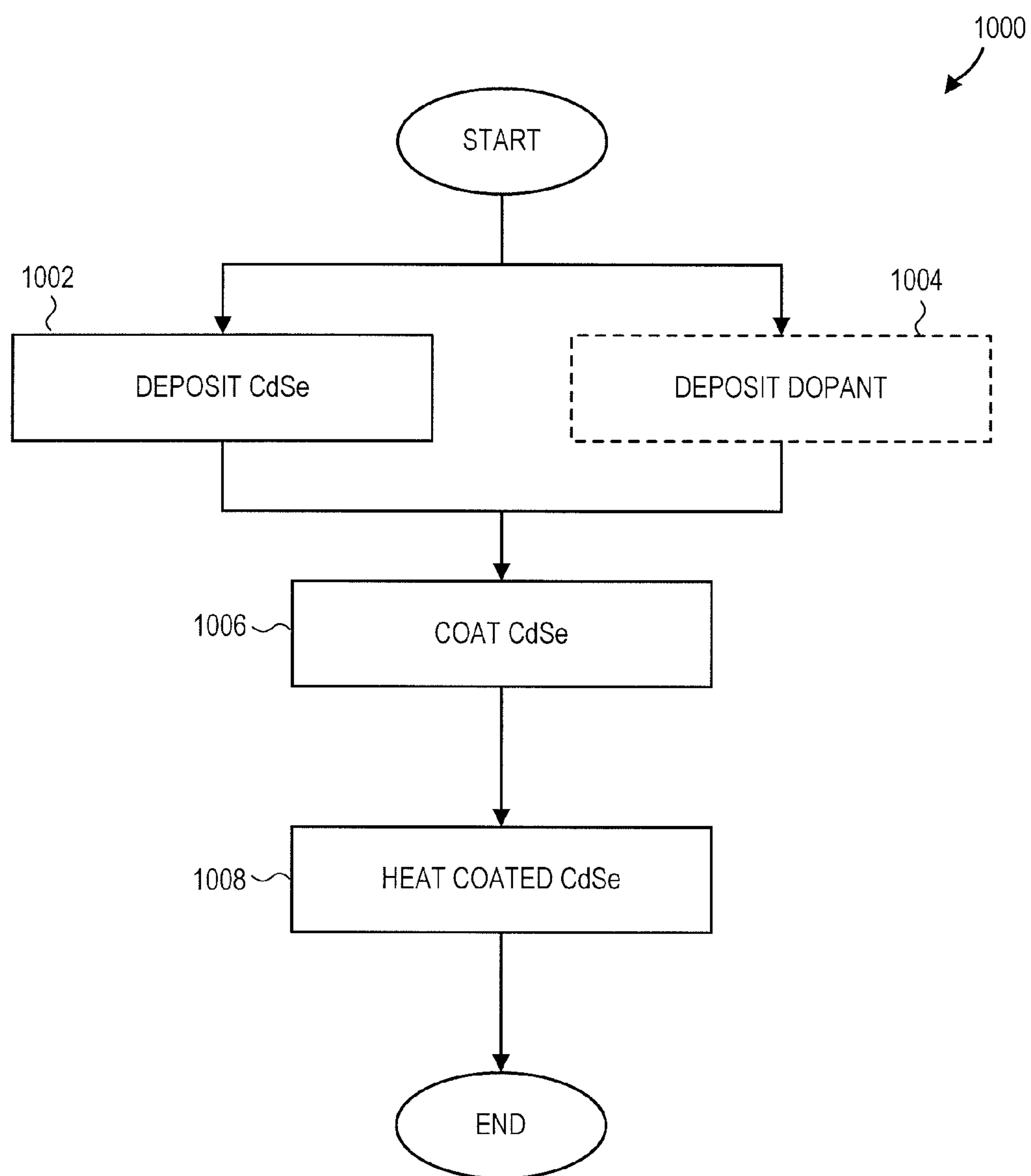


FIG. 10

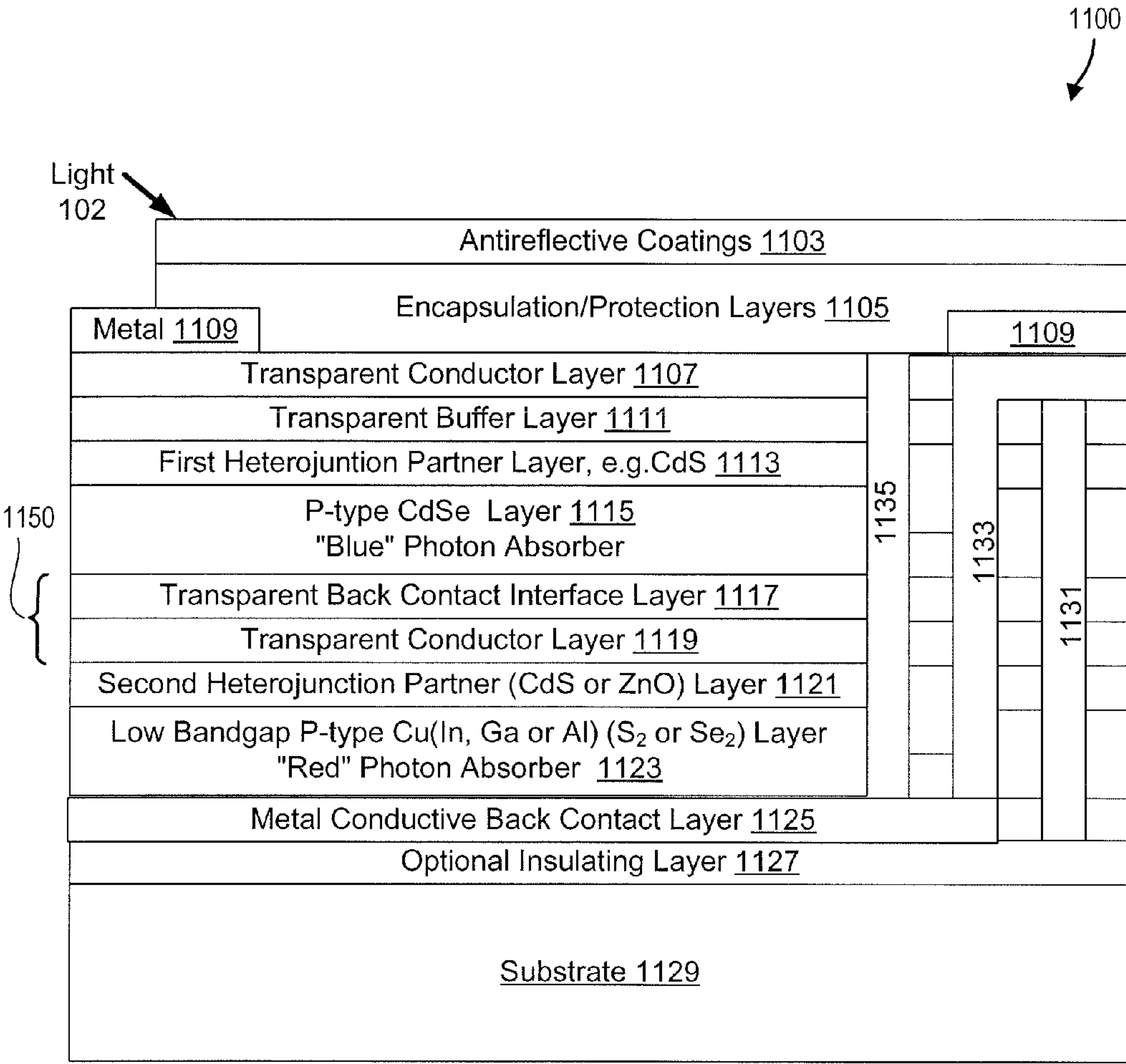


FIG. 11

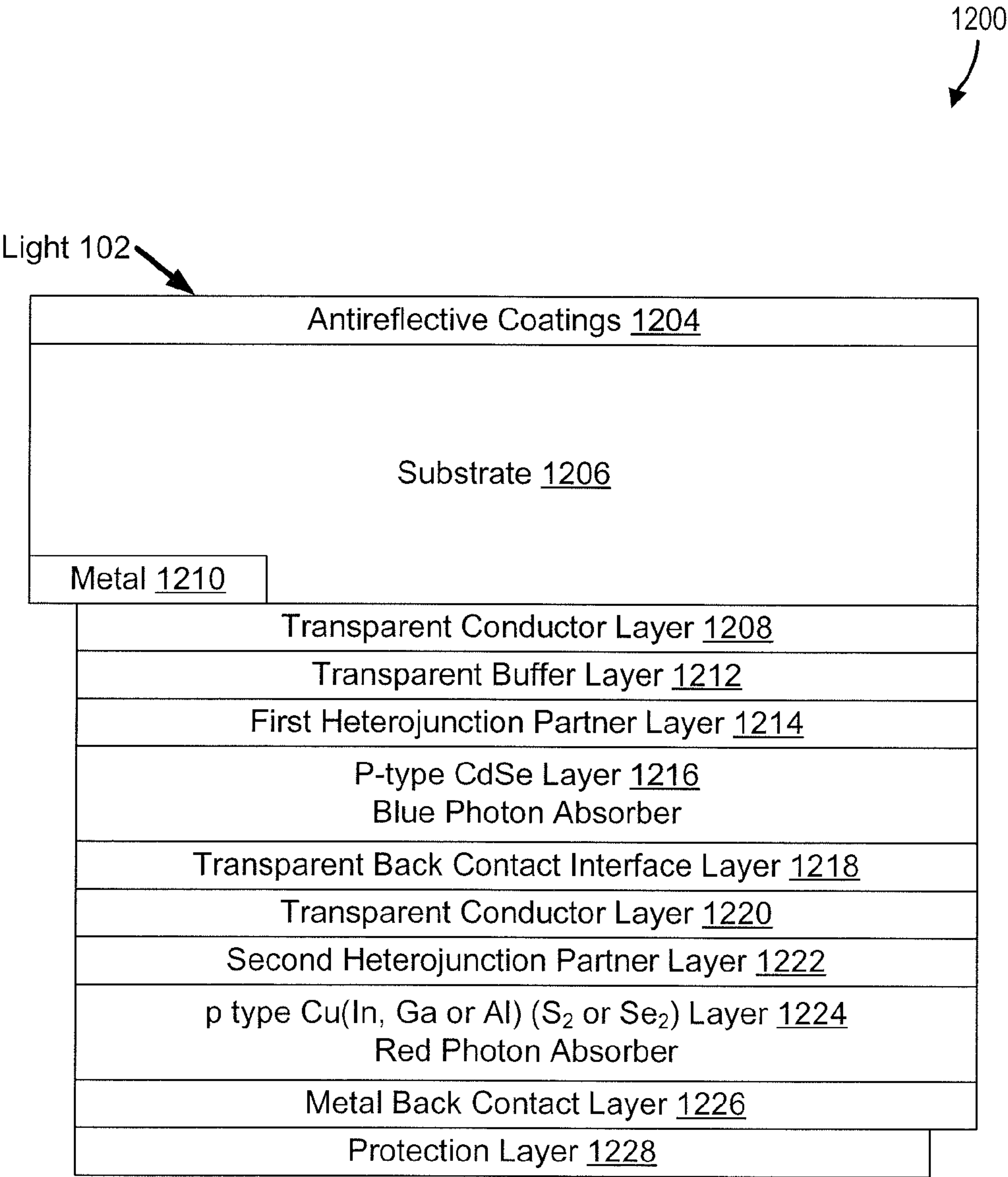


FIG. 12

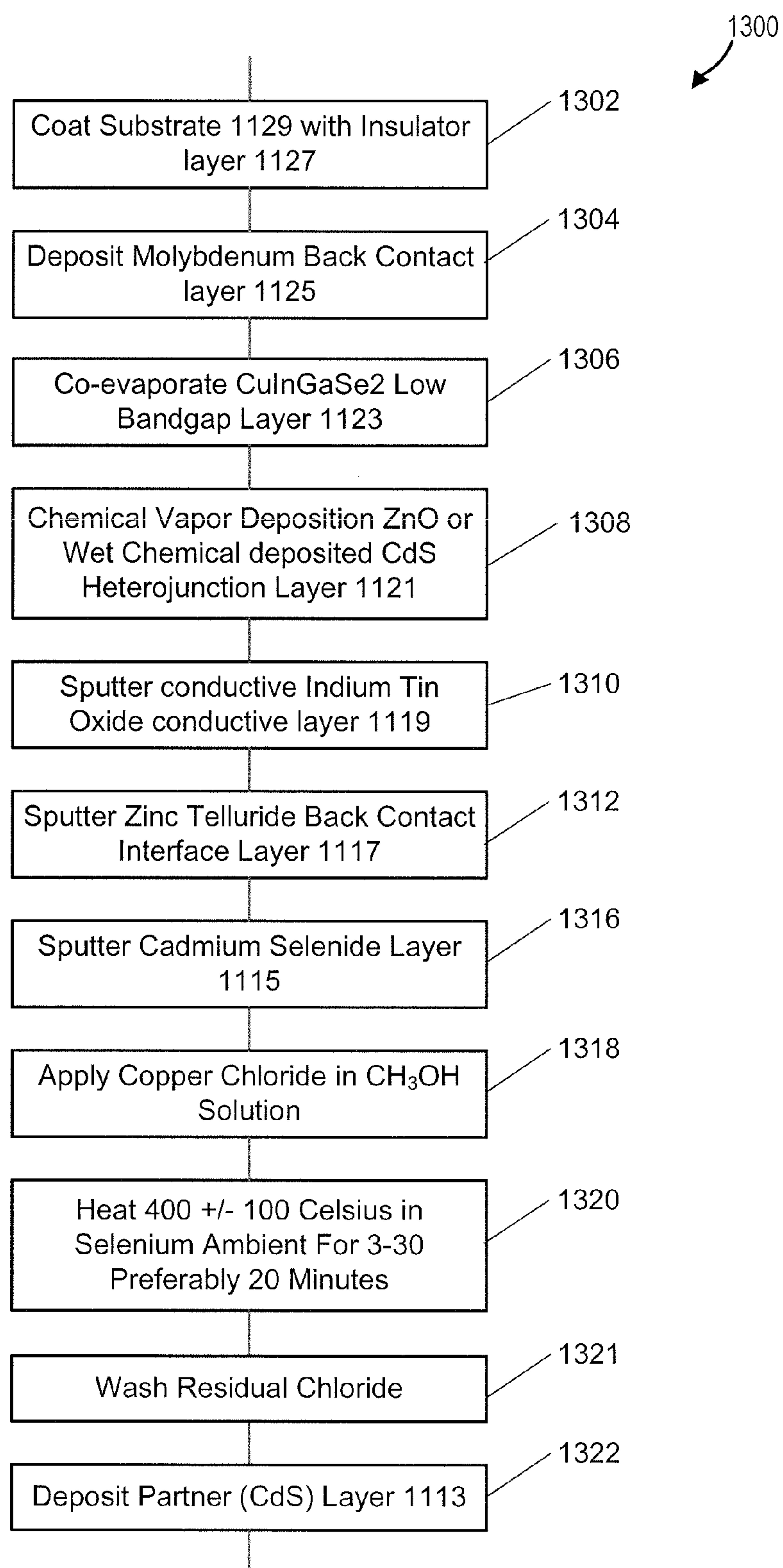


FIG. 13

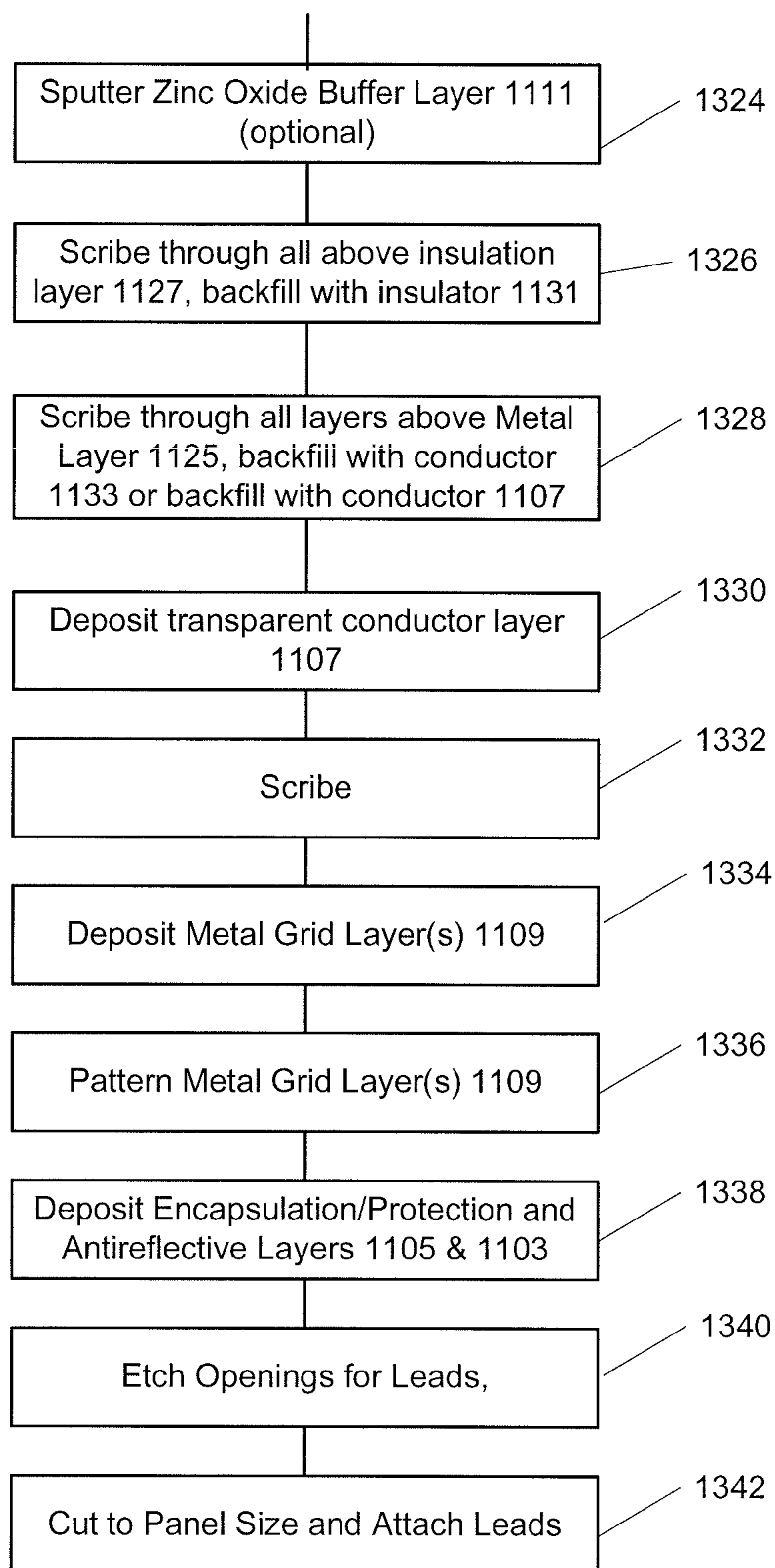


FIG. 14

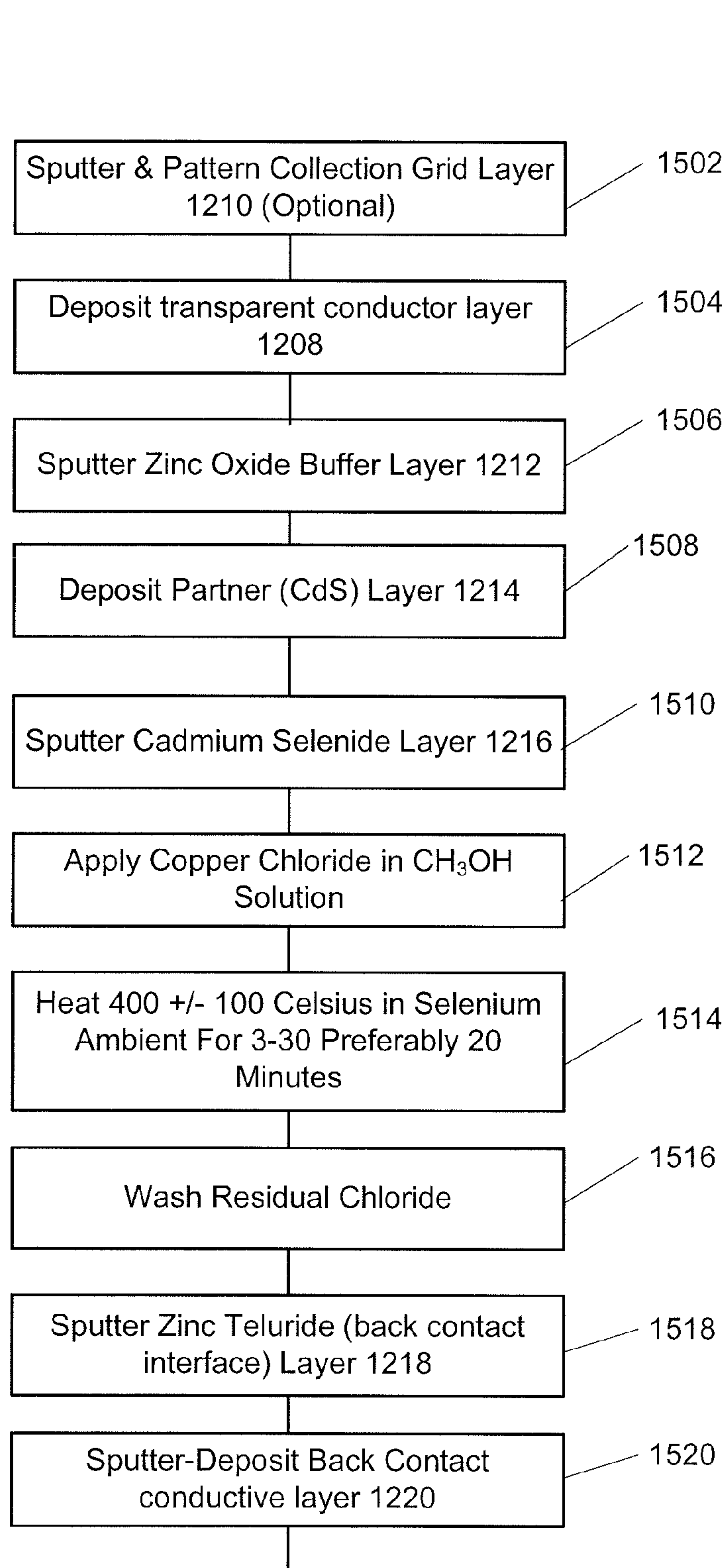


FIG. 15

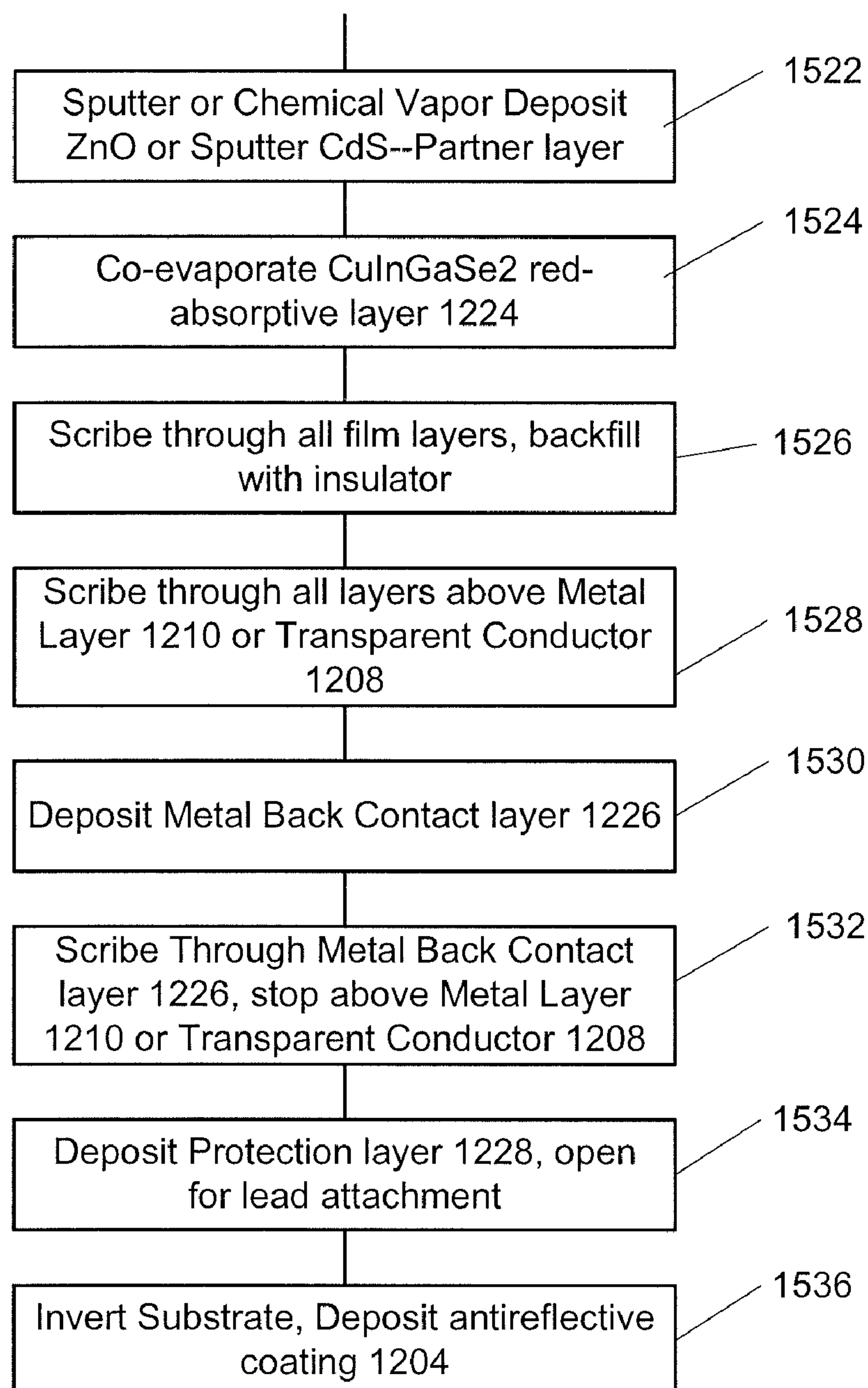


FIG. 16

HYBRID MULTI-JUNCTION PHOTOVOLTAIC CELLS AND ASSOCIATED METHODS

CROSS REFERENCE TO RELATED APPLICATIONS

[0001] This application claims benefit of priority of U.S. Provisional Patent Application Ser. No. 60/950,087 filed 16 Jul. 2007, U.S. Provisional Patent Application Ser. No. 60/956,107 filed 15 Aug. 2007, and U.S. Provisional Patent Application Ser. No. 61/031,652 filed 26 Feb. 2008. All of the aforementioned applications are hereby incorporated herein by reference.

U.S. GOVERNMENT RIGHTS

[0002] Certain claims with this invention were made with Government support under Advanced Technical Program Grant No. 70NANB8H4070 awarded by the United States Department of Commerce (NIST), and a Small-Business Innovative Research program contract No. FA9453-03-C-0216 awarded by the United States Department of Defense. The Government has certain rights in this invention.

BACKGROUND

[0003] Photovoltaic cells convert electromagnetic energy (e.g., sunlight) into an electric current; accordingly, they are commonly used to provide electric power in a diverse range of applications. For example, photovoltaic cells may be incorporated in and provide electric power for devices as diverse as hand-held calculators and space vehicles.

[0004] Photovoltaic cells having a variety of characteristics have been developed. One class of photovoltaic cells that is currently the subject of significant research is the thin-film class. Thin-film photovoltaic cells include a plurality of layers of thin films formed on a substrate.

[0005] As mentioned above, photovoltaic cells (e.g., thin-film photovoltaic cells) may be operated from sunlight. Sunlight generally includes a plurality of colors of light, including light in the infrared and near ultraviolet bands, where each color of light has a different energy. For example, blue light has greater energy per photon than red light.

[0006] It is known that absorption of light in a photovoltaic cell typically requires that each photon have energy greater than the bandgap energy of the absorbing material, such that carriers can be excited into the free or nearly free carrier bands (conduction and valence) in the absorbing material. These carriers then move to appropriate sides of the junction, providing an output voltage and current. Absorbed photon energy in excess of this bandgap energy is usually wasted in that additional carriers are not always generated. Semiconductor materials that have electrons as the dominant free carriers are defined as n-type materials, and materials that have holes, or the absence of an electron, as the dominant free carriers are defined as p-type materials.

[0007] The maximum output voltage of the cell is related to the bandgap of the materials used to form the junction. For example, higher bandgap materials can provide higher output voltages. As a result, photovoltaic cells optimized to absorb long wavelength, or low energy, photons will also absorb short-wavelength photons, but will waste much energy by producing a lower output voltage than attainable with cells optimized to absorb the short wavelength, high energy, photons.

[0008] A photovoltaic cell optimized to absorb short wavelength, e.g. blue, light will fail to efficiently absorb long wavelength, or red and infrared, light because the bandgap of the material is greater than the available energy in each photon, and therefore, photons are not absorbed and carriers are not promoted into the conduction.

SUMMARY

[0009] In an embodiment, a photovoltaic cell includes a transparent conductor layer, a first heterojunction partner layer, a p-type Cadmium Selenide layer in contact with the first heterojunction partner layer, and a first electrical contact layer.

[0010] In an embodiment, a hybrid multi-junction photovoltaic cell includes a substrate for providing mechanical support for the photovoltaic cell. The substrate is a polymer substrate. A back contact layer is formed on the substrate, and a bottom solar absorber layer is formed on the back contact layer. The bottom solar absorber layer includes one of the following materials: a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character, and an alloy of a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character. A heterojunction partner layer is formed on the bottom solar absorber layer, and a layer of p-type semiconductor is formed above the heterojunction partner layer. A layer of intrinsic semiconductor is formed on the layer of p-type semiconductor, and a layer of n-type semiconductor is formed on the layer of intrinsic semiconductor.

[0011] In an embodiment, a module of a plurality of hybrid multi-junction photovoltaic cells includes a substrate for providing mechanical support for the photovoltaic cells and a back contact layer formed on the substrate. A bottom solar absorber layer is formed on the back contact layer, and the bottom solar absorber layer includes one of the following materials: a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character, and an alloy of a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character. An n-type heterojunction partner layer is formed on the bottom solar absorber layer, and a contact layer of p-type semiconductor is formed above the heterojunction partner layer. A primary solar absorber layer is formed on the contact layer of p-type semiconductor, and the primary solar absorber layer is formed of an intrinsic semiconductor or a p-type semiconductor. A layer of n-type semiconductor is formed on the primary solar absorber layer, and a top contact layer is formed on the layer of n-type semiconductor. At least one first isolating scribe extends at least from a top surface of the layer of n-type semiconductor to a top surface of the substrate, and the first isolating scribe is filled with an insulating material. At least one connecting scribe extends at least from the top surface of the layer of n-type semiconductor to a top surface of the back contact layer, and the connecting scribe is filled with a conductive material. At least one second isolating scribe extends at least from a top surface of the top contact layer to a top surface of the bottom solar absorber layer.

[0012] In an embodiment, a multi-junction photovoltaic cell includes a substrate for providing mechanical support for the photovoltaic cell and a back contact layer formed on the substrate. A solar absorber layer is formed on the back contact layer, and the solar absorber layer is formed of a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character. A heterojunction partner layer is formed on the solar absorber layer, and the heterojunction partner layer includes at least one layer of a high resistivity material having a resistivity of

at least 100 ohms-centimeter. The high resistivity material has the formula (Zn and/or Mg)(S, Se, O, and/or OH). A conductive interconnect layer is formed above the heterojunction partner layer, and at least one additional single-junction photovoltaic cell is formed on the conductive interconnect layer.

[0013] In an embodiment, a method of making a p-type Cadmium Selenide semiconductor material includes depositing a layer of Cadmium Selenide and coating the layer of Cadmium Selenide with a solution. The solution includes a solvent and at least one of the following chlorides: chlorides of Group IA elements, chlorides of group IB elements, and chlorides of Group IIIB elements. The coated layer of Cadmium Selenide is heated in an environment having an ambient temperature of between 300 and 500 degrees Celsius for a time between three and thirty minutes while at least partially preventing the evaporation of Selenium from the coated layer of Cadmium Selenide.

[0014] In an embodiment, a method of making a photovoltaic device includes depositing a contact layer, depositing a layer of Cadmium Selenide, and coating the layer of Cadmium Selenide with a solution. The solution includes a solvent and at least one of the following chlorides: chlorides of Group IA elements, chlorides of group IB elements, and chlorides of Group IIIB elements. The coated layer of Cadmium Selenide is heated in an environment having an ambient temperature of between 300 and 500 degrees Celsius for a time between three and thirty minutes while at least partially preventing the evaporation of Selenium from the coated layer of Cadmium Selenide. A heterojunction partner layer is deposited, and a transparent conductor layer is deposited.

[0015] In an embodiment, a method of making a photovoltaic device includes depositing a transparent conductor layer, depositing a heterojunction partner layer, and depositing a layer of Cadmium Selenide. The layer of Cadmium Selenide is coated with a solution including a solvent and at least one of the following chlorides: chlorides of Group IA elements, chlorides of group IB elements, and chlorides of Group IIIB elements. The coated layer of Cadmium Selenide is heated in an environment having an ambient temperature of between 300 and 500 degrees Celsius for a time between three and thirty minutes while at least partially preventing the evaporation of Selenium from the coated layer of Cadmium Selenide. A contact layer is deposited.

[0016] In an embodiment, a process for forming a hybrid multi-junction photovoltaic cell includes forming a first single-junction photovoltaic cell on a substrate. The step of forming the first single-junction photovoltaic cell includes: (1) forming a first back contact layer on the substrate, (2) forming a first solar absorber layer on the back contact layer, the first solar absorber layer being formed of a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character, and (3) forming a first heterojunction partner layer on the first solar absorber layer, the first heterojunction partner layer including at least one layer of a high resistivity material having a resistivity of at least 100 ohms-centimeter, the high resistivity material being a material having the formula (Zn and/or Mg)(S, Se, O, and/or OH). A conductive interconnect layer is formed above the first heterojunction partner layer of the first single-junction photovoltaic cell. At least one additional single-junction photovoltaic cell is formed above the conductive interconnect layer.

BRIEF DESCRIPTION OF DRAWINGS

[0017] FIG. 1 is a top perspective view of one module of photovoltaic cells, in accordance with one embodiment.

[0018] FIG. 2 is a cross sectional view of one photovoltaic cell, in accordance with one embodiment.

[0019] FIG. 3 is a cross sectional view of one two-junction photovoltaic cell, in accordance with one embodiment.

[0020] FIG. 4 is a cross sectional view of one three-junction photovoltaic cell, in accordance with one embodiment.

[0021] FIG. 5 is a graph of idealized spectral response versus wavelength of electromagnetic energy of an embodiment of the photovoltaic cell of FIG. 3.

[0022] FIG. 6 is a cross sectional view of one multi-junction photovoltaic cell, in accordance with one embodiment.

[0023] FIG. 7 is a cross sectional view of one multi-junction photovoltaic cell, in accordance with one embodiment.

[0024] FIG. 8 is a cross sectional view of one multi-junction photovoltaic cell, in accordance with one embodiment.

[0025] FIG. 9 is a cross sectional view of a plurality of multi-junction photovoltaic cells monolithically integrated onto a common substrate, in accordance with one embodiment.

[0026] FIG. 10 shows one method of converting n-type Cadmium Selenide to p-type Cadmium Selenide, in accordance with one embodiment.

[0027] FIG. 11 is a cross sectional view of one two-junction photovoltaic cell, in accordance with one embodiment.

[0028] FIG. 12 is a cross sectional view of one two-junction photovoltaic cell, in accordance with one embodiment.

[0029] FIGS. 13 and 14 show one method of fabricating the photovoltaic cell of FIG. 11, in accordance with one embodiment.

[0030] FIGS. 15 and 16 show one method of fabricating the photovoltaic cell of FIG. 12, in accordance with one embodiment.

DETAILED DESCRIPTION OF THE EMBODIMENTS

[0031] It is noted that, for purposes of illustrative clarity, certain elements in the drawings may not be drawn to scale. Specific instances of an item may be referred to by use of a numeral in parentheses (e.g., photovoltaic cell 108(1)) while numerals without parentheses refer to any such item (e.g., photovoltaic cells 108).

[0032] FIG. 1 is a top perspective view of one module 100 of photovoltaic cells 108. Although module 100 is illustrated as having six photovoltaic cells 108, module 100 may have any quantity of photovoltaic cells. Furthermore, although photovoltaic cells 108 are illustrated in FIG. 1 as having a rectangular shape, photovoltaic cells 108 can have other shapes (e.g., a square or circle). Photovoltaic cells 108 are operable to convert electromagnetic energy 102 (e.g., sunlight) into an electric current. If module 100 includes several photovoltaic cells 108, the cells may be electrically connected in series to increase the voltage of module 100, in parallel to increase the maximum current capability of module 100, or in combinations of parallel and series to increase both the voltage and maximum current capability of module 100. The electric current generated by photovoltaic cells 108 is accessible via electrical terminals 104 and 106.

[0033] Photovoltaic cells 108 are thin-film photovoltaic cells; that is, photovoltaic cells 108 are formed of a plurality of thin-film layers on a substrate. In embodiments of module 100, several photovoltaic cells 108 are formed on a single common substrate; in such cases, the several photovoltaic cells 108 are considered to be "monolithically integrated" on the substrate.

[0034] FIG. 2 is a cross sectional view of one photovoltaic cell 200. Photovoltaic cell 200 is an embodiment of photovoltaic cell 108 of FIG. 1. Photovoltaic cell 200 as illustrated in FIG. 2 is a single-junction photovoltaic cell; however, photovoltaic cell 200 may be combined with one or more additional single-junction photovoltaic cells to form a multi-junction photovoltaic cell, as discussed below. Furthermore, several photovoltaic cells 200 may be monolithically integrated onto substrate 202. Photovoltaic cell 200 absorbs electromagnetic energy 102 incident on its top surface 214.

[0035] Substrate 202 forms a base and provides mechanical support for photovoltaic cell 200. Substrate 202 affects characteristics of photovoltaic cell 200; accordingly, substrate 202 is chosen in accordance with the required characteristics of photovoltaic cell 200. For example, if photovoltaic cell 200 is to be flexible, substrate 202 must be flexible. As another example, if photovoltaic cell 200 is not to be electrically shorted to adjacent cells on the same substrate, substrate 202 should have an insulating surface. Further, if photovoltaic cell 200 is to be able to withstand high processing temperatures, substrate 202 must be able to withstand such high processing temperatures. Examples of materials that may be used to form substrate 202 include one of a polymer material (e.g., polyimide), a reinforced polymer material (e.g. carbon-fiber or glass-fiber reinforced polymer), metal foil, insulated metal foil (e.g., polymer coated metal foil), and glass.

[0036] Back contact layer 204 is formed on substrate 202. Back contact layer 204 provides electrical interface to photovoltaic cell 200. Back contact layer 204 is formed of a material that is compatible with (e.g., forms a good contact with) solar absorber layer 206; in an embodiment, back contact layer 204 includes molybdenum.

[0037] Solar absorber layer 206 is formed on back contact layer 204; solar absorber layer 206 is formed of a material having bulk p-type character. The term bulk p-type character means that at least a majority of the material is p-type. However, portions (e.g., a surface or a near surface, or doped portions) of a material having a bulk p-type character may not be p-type. For example, a surface of a material having a bulk p-type character may be n-type.

[0038] Solar absorber layer 206 has a photovoltaic effect such that solar absorber layer 206 is operable to at least partially absorb electromagnetic energy 102 having a certain range of wavelengths and create corresponding electron-hole pairs. In an embodiment, solar absorber layer 206 is formed of a Group IB-IIIB-VIB₂ material having bulk p-type character. The term Group IB-IIIB-VIB₂ material refers to a compound having a photovoltaic effect that is formed of at least one element from each of Groups IB, IIIB, and VIB of the periodic table, wherein there are typically two atoms of the Group VIB element for every one atom of the Group IB and IIIB elements. In the context of this disclosure, Group IB elements include Copper, Silver, and Gold; Group IIIB elements include Boron, Aluminum, Gallium, Indium, and Thallium; and Group VIB elements include Oxygen, Sulfur, Selenium, and Tellurium. Examples of materials that may be used to form solar absorber layer 206 therefore include Copper Indium DiSelenide, Copper Indium DiTelluride, an alloy formed of Copper Indium DiSelenide and at least one of Gallium, Aluminum, and Sulfur (e.g., Copper Indium Gallium DiSelenide), and an alloy formed of Copper Indium DiTelluride and at least one of Gallium, Aluminum, and Sulfur. In an embodiment, solar absorber layer 206 is formed of a low bandgap p-type Group IB-IIIB-VIB₂ material. A low

bandgap material for purposes of this disclosure and the corresponding claims is a material that is tuned to absorb electromagnetic energy in the red and/or infrared portions of the electromagnetic spectrum. An embodiment of photovoltaic cell 200 having solar absorber layer 206 formed of a low bandgap material may be useful if photovoltaic cell 200 is combined with another single-junction photovoltaic cell tuned to absorb electromagnetic energy of a different portion of the electromagnetic spectrum (e.g., ultraviolet or blue light). In an embodiment, solar absorber layer 206 is formed using at least one of a sequential selenization process, a sulfurization process, a tellurization process, a thermal evaporation process, an electron beam evaporation process, a sputtering process, an electrodeposition process, a molecular beam epitaxy process, and a chemical vapor deposition process.

[0039] As another example, solar absorber layer 206 may be formed of Cadmium Selenide having a bulk p-type character ("p-type Cadmium Selenide"). Such p-type Cadmium Selenide may be obtained by converting n-type Cadmium Selenide to p-type as discussed below with respect to FIG. 10. For purposes of this disclosure and the corresponding claims, Cadmium Selenide is a material that is tuned to absorb electromagnetic energy in the red/yellow to blue and ultraviolet portions of the electromagnetic spectrum. An embodiment of photovoltaic cell 200 having solar absorber layer 206 formed of a Cadmium Selenide material may be useful if photovoltaic cell 200 is combined with another single-junction photovoltaic cell tuned to absorb electromagnetic energy of a different portion of the electromagnetic spectrum (e.g., red and infrared light).

[0040] Window layer or heterojunction partner layer 208 is formed on solar absorber layer 206. Heterojunction partner layer 208, for example, forms a heterojunction with the material of solar absorber layer 206 having bulk p-type character. Heterojunction partner layer 208 is, for example, formed of a high resistivity material having the formula (Zn and/or Mg) (S, Se, O, and/or OH) where the material may be formed of any combination of Zn and/or Mg, and one or more of S, Se, O, or OH. In an embodiment, heterojunction partner layer 208 is formed of Zinc Oxide. In another embodiment, heterojunction partner layer 208 is formed of a Zinc Magnesium Oxide alloy. Forming heterojunction partner layer 208 of such materials may advantageously help photovoltaic cell 200 to withstand higher processing temperatures than some other heterojunction partner layer materials, as discussed below. In the context of this disclosure and corresponding claims, the term high resistivity means a resistivity of at least 100 ohms-centimeter. In embodiments, heterojunction partner layer 208 has a resistivity of at least 1,000 ohms-centimeter. Forming heterojunction partner layer 208 of a high resistivity Zn compound (e.g., Zinc Oxide, Zinc Magnesium Oxide) may advantageously improve the high-temperature durability of photovoltaic cell 200 over a photovoltaic cell with a Zn compound having a lower resistivity. In an embodiment, heterojunction partner layer 208 is preferably formed using a chemical vapor deposition process (e.g., metal-organic chemical vapor deposition) such that a top surface of solar absorber layer 206 is not damaged by the deposition process.

[0041] As another example, heterojunction partner layer 208 may be formed of Cadmium Sulfide, such as when solar absorber layer 206 is formed of p-type Cadmium Selenide.

[0042] Photovoltaic cell 200 optionally includes buffer layer 210 formed on heterojunction partner layer 208; an

exemplary material that may be used to form buffer layer **210** is undoped Zinc Oxide. Conductive top contact layer or interconnect layer **212** is formed on buffer layer **210**, if present, or is formed on heterojunction partner layer **208** if buffer layer **210** is not present. Layer **212** is referred to as a top contact layer if photovoltaic cell **200** is not combined with an additional photovoltaic cell. Layer **212** is referred to as an interconnect layer if photovoltaic cell **200** is combined with one or more additional single-junction photovoltaic cells **200** to form a multi-junction photovoltaic cell; in such case interconnect layer **212** provides electrical connection between photovoltaic cell **200** and an additional single-junction photovoltaic cell formed on top surface **214** of photovoltaic cell **200**. Top contact/interconnect layer **212** is electrically conductive and is at least partially transparent to electromagnetic energy **102** in order to allow electromagnetic energy **102** to reach solar absorber layer **206**. Exemplary materials that may be used to form top contact/interconnect layer **212** include doped Zinc Oxide, undoped Zinc Oxide, Indium Tin Oxide, doped Tin Oxide, undoped Tin Oxide, n-type amorphous Silicon, n-type amorphous Silicon Germanium, hydrogenated amorphous Silicon carbide, and n-type microcrystalline amorphous Silicon.

[0043] One embodiment of photovoltaic cell **200** has the following configuration: substrate **202** formed of glass, back contact layer **204** formed of molybdenum, solar absorber layer **206** formed of Copper Indium DiSelenide, heterojunction partner layer **208** formed of Zinc Oxide, buffer layer **210** formed of Zinc Oxide, and top contact/interconnect layer **212** formed of Indium Tin Oxide.

[0044] As stated above, in embodiments, heterojunction partner layer **208** is formed of a high resistivity material having the formula $(\text{Zn and/or Mg})(\text{S, Se, O, and/or OH})$. This heterojunction partner layer construction may result in photovoltaic cell **200** having a greater ability to withstand heat and/or vacuum stresses than some other thin-film photovoltaic cells. For example, in a thin-film photovoltaic cell including a solar absorber layer formed Copper Indium DiSelenide or Copper Indium DiTelluride and a heterojunction partner layer (window layer) formed of Cadmium Sulfide, heat and/or vacuum stresses may result in excessive cross-diffusion of constituent elements of the solar absorber layer and the heterojunction partner layer across their junction. This cross-diffusion causes degradation of the junction and overall performance of the photovoltaic cell; accordingly, such photovoltaic cell has a relatively low ability to withstand heat and vacuum stresses. However, if heterojunction partner layer **208** is formed of a high resistivity material having the formula $(\text{Zn and/or Mg})(\text{S, Se, O, and/or OH})$, junction degradation may be reduced or eliminated.

[0045] Forming heterojunction partner layer **208** of a high resistivity material having the formula $(\text{Zn and/or Mg})(\text{S, Se, O, and/or OH})$ also may allow photovoltaic cell **200** to have a greater ability to operate from electromagnetic energy including little or no blue colored light compared to some other thin-film photovoltaic cells. For example, a thin-film photovoltaic cell including a solar absorber layer formed from Copper Indium DiSelenide or Copper Indium DiTelluride and a heterojunction partner layer formed of Cadmium Sulfide generally performs better when the electromagnetic energy incident upon the window layer contains at least some blue colored light. This requirement is due to defects in the Cadmium Sulfide. However, this problem can be avoided by

forming heterojunction partner layer **208** of a high resistivity material having the formula $(\text{Zn and/or Mg})(\text{S, Se, O, and/or OH})$.

[0046] Forming an additional photovoltaic cell on a first photovoltaic cell commonly exposes the first photovoltaic cell to significant heat and/or vacuum stresses. Additionally, one or more additional photovoltaic cells formed on the first photovoltaic cell often blocks transmission of blue electromagnetic energy to the first photovoltaic cell. Accordingly, photovoltaic cell **200** may be an attractive photovoltaic cell for use as a bottom photovoltaic cell in a multi-junction photovoltaic cell due to photovoltaic cell **200**'s relatively low sensitivity to heat and vacuum stresses and ability to reliably operate from electromagnetic energy devoid of blue light.

[0047] A multi-junction photovoltaic cell includes two or more single-junction photovoltaic cells optically aligned with each other, and each of the single-junction photovoltaic cells is tuned to respond to (i.e., absorb) electromagnetic energy having a different range of wavelengths. For example, FIG. 3 is a cross sectional view of one two-junction photovoltaic cell **300**, and FIG. 4 is a cross sectional view of one three-junction photovoltaic cell **400**. Two or more of the single-junction photovoltaic cells in a multi-junction photovoltaic cell may have different solar absorber layer materials; in such case, the multi-junction photovoltaic cell may be referred to as a hybrid photovoltaic cell.

[0048] A two junction or tandem photovoltaic cell **300** includes a second single-junction photovoltaic cell **304** formed on a first single-junction photovoltaic cell **302**. Each of first and second photovoltaic cells **302** and **304** are designed to absorb portions of electromagnetic energy **102** having different ranges of wavelengths. FIG. 5, which is a graph **500** of idealized spectral response versus wavelength, illustrates one possible design of two-junction photovoltaic cell **300**. A vertical axis **502** represents the magnitude of the spectral response of a photovoltaic cell; the spectral response essentially represents the photovoltaic cell's conversion of electromagnetic energy into an electric current. A horizontal axis **504** represents wavelength of electromagnetic energy. A curve **506** represents the spectral response of second photovoltaic cell **304** as a function of wavelength of electromagnetic energy, and a curve **508** represents the spectral response of first photovoltaic cell **302** as a function of wavelength of electromagnetic energy. As can be observed from FIG. 5, in an embodiment of two-junction photovoltaic cell **300** designed according to FIG. 5, second photovoltaic cell **304** responds to electromagnetic energy having a shorter wavelength than first photovoltaic cell **302**. For example, second photovoltaic cell **304** may respond to (that is convert to an electric current), light generally having a blue color while first photovoltaic cell **302** responds to light generally having a red and/or infrared color. Thus, two-junction photovoltaic cell **300** is operable to generate an electric current from electromagnetic energy having two ranges of wavelengths as illustrated by curves **506** and **508**.

[0049] In photovoltaic cell **300**, electromagnetic energy **102** impinges a top surface **308** of photovoltaic cell **300**; a portion of electromagnetic energy **102** having a certain range of wavelengths is absorbed by second photovoltaic cell **304** and is converted to an electric current. A portion of electromagnetic energy **102** that is not absorbed by second photovoltaic cell **304** passes to first photovoltaic cell **302** as indicated by arrows **306**.

[0050] Three-junction photovoltaic cell 400 includes a third single-junction photovoltaic cell 406 formed on a second single-junction photovoltaic cell 404 which is in turn formed on a first single-junction photovoltaic cell 402. Each of first, second, and third single junction photovoltaic cells 402, 404, and 406 is designed to absorb portions of electromagnetic energy 102 having different ranges of wavelengths. Electromagnetic energy 102 impinges a top surface 412 of photovoltaic cell 400; a portion of electromagnetic energy 102 having a certain range of wavelengths is absorbed by third photovoltaic cell 406 and converted to an electric current. A portion of electromagnetic energy 102 that is not absorbed by third photovoltaic cell 406 passes to second photovoltaic cell 404 as indicated by arrows 410. Second photovoltaic cell 404 absorbs a portion of a certain range of wavelengths of electromagnetic energy 410, and the remainder of electromagnetic energy 410 passes to first photovoltaic cell 402 as indicated by arrows 408. A portion of electromagnetic energy 408 having a certain range of wavelengths is absorbed by first photovoltaic cell 402.

[0051] A multi-junction photovoltaic cell may have advantages over a single-junction photovoltaic cell. First, as discussed above with respect to FIGS. 3-5, a multi-junction photovoltaic cell has a plurality of single-junction photovoltaic cells each of which are tuned to respond to electromagnetic energy having a certain range of wavelengths. Accordingly, there may be a smaller difference between the energy level of at least some of the electromagnetic energy spectrum that creates 'free' electron-hole pairs in a solar absorber layer and the bandgap energy of the solar absorber layer in a multi-junction photovoltaic cell than in a single-junction photovoltaic cell. Therefore, a multi-junction photovoltaic cell may have a smaller energy loss due to thermalization of free carriers with excess energy above a solar absorber layer's bandgap energy level than a single-junction photovoltaic cell. As a result, a multi-junction photovoltaic cell may operate more efficiently than a single-junction photovoltaic cell.

[0052] Second, a multi-junction photovoltaic cell generally has a higher output voltage than a single-junction photovoltaic cell. This may be advantageous because the higher output voltage reduces the output current required to power a given load. Reducing the output current magnitude reduces resistive losses which directly increases the efficiency of the solar cell and module. Also, a multi-junction photovoltaic cell generally has a lower temperature coefficient than a single-junction photovoltaic cell, where the temperature coefficient quantifies additional power loss in the photovoltaic cell due to an increase in the photovoltaic cell's operating temperature. A lower temperature coefficient is beneficial because it reduces the power loss of the photovoltaic cell at elevated operating temperatures, which commonly occur in practical photovoltaic cell applications. Furthermore, increasing the output voltage of a photovoltaic cell may be advantageous in that it reduces the quantity of photovoltaic cells that must be electrically connected in series in order to provide a required output voltage. Reducing the quantity of series connected photovoltaic cells may in turn reduce monolithic integration cost and area of a module lost due to electrical interconnection of photovoltaic cells.

[0053] FIG. 6 is a cross sectional view of one multi-junction photovoltaic cell 600. Photovoltaic cell 600, which is an embodiment of photovoltaic cell 108, includes a second single-junction photovoltaic cell 602 formed on photovoltaic cell 200. Although photovoltaic cell 600 is illustrated in FIG.

6 as being a two-junction photovoltaic cell, photovoltaic cell 600 may have more than two junctions. For example, photovoltaic cell 600 could be a three-junction photovoltaic cell if a third single-junction photovoltaic cell were formed on a top surface 606 of second photovoltaic cell 602. Multiple photovoltaic cells 600 may be monolithically integrated onto substrate 202; and one or more substrates 202 with cells may be combined into a module or solar panel.

[0054] As discussed above with respect to FIG. 2, photovoltaic cell 200 may optionally include a buffer layer (not shown in FIG. 6) disposed between heterojunction partner layer 208 and interconnect layer 212. In addition to providing an interface between photovoltaic cell 200 and second photovoltaic cell 602 (FIG. 6), an embodiment of interconnect layer 212 may reflect some electromagnetic energy that passes through second photovoltaic cell 602 back into second photovoltaic cell 602 for absorption by it. As discussed above, embodiments of photovoltaic cell 200 may withstand higher temperatures and/or vacuum stresses better than some other thin-film photovoltaic cells; accordingly, it is desirable that photovoltaic cell 200 can withstand deposition of at least one additional photovoltaic cell (e.g., second photovoltaic cell 602) on top surface 608 of interconnect layer 212. Additionally, as discussed above, certain embodiments of bottom photovoltaic cell 200 do not need to absorb blue colored light in order to operate well. Accordingly, photovoltaic cell 200 may operate well even if second photovoltaic cell 602 (and any additional single-junction photovoltaic cells) absorbs some or all of the blue light of electromagnetic energy 102.

[0055] Second photovoltaic cell 602 is tuned to be complementary to photovoltaic cell 200. For example, second photovoltaic cell 602 is optimized to absorb a certain range of wavelengths of electromagnetic energy that first photovoltaic cell 200 is not optimized to absorb. Examples of second photovoltaic cells 602 include a solar absorber layer formed of a material including one of a Cu(In, Ga, Al)Se₂ compound, a Cu(In, Ga, Al)S₂ compound, amorphous Silicon (e.g., hydrogenated amorphous Silicon), a hydrogenated amorphous Silicon Germanium alloy, a (Cd, Zn, Mg, Mn)Te compound, and p-type Cadmium Selenide. By a Cu (In, Ga, Al) Se₂ compound, a compound is meant that comprises Copper, Selenium, and at least one of Indium, Gallium, or Aluminum. By a Cu(In, Ga, Al)S₂ compound, a compound is meant that comprises Copper, Sulfur, and at least one of Indium, Gallium, or Aluminum. By a (Cd, Zn, Mg, Mn)Te compound, a compound is meant that comprises Tellurium and at least one of Cadmium, Zinc, Magnesium, or Manganese.

[0056] FIG. 7 is a cross sectional view of one multi-junction photovoltaic cell 700, which is an embodiment of photovoltaic cell 600. Photovoltaic cell 702 is an embodiment of photovoltaic cell 602. A plurality of photovoltaic cells 700 may be monolithically integrated onto substrate 202.

[0057] Second photovoltaic cell 702 optionally includes a second back contact layer 706 formed on interconnect layer 212. Second back contact layer 706 is at least partially transparent to electromagnetic energy having a certain range of wavelengths intended to be absorbed by solar absorber layer 206 of photovoltaic cell 200. If second back contact layer 706 is not included in photovoltaic cell 700, interconnect layer 212 serves as a back contact for photovoltaic cell 702.

[0058] Second solar absorber layer 708 is formed on second back contact layer 706 (or an interconnect layer 212 if second back contact layer 706 is not present). In an embodiment, solar absorber layer 708 is formed of a material includ-

ing one of a Cu(In, Ga, Al)Se₂ compound, a Cu(In, Ga, Al)S₂ compound, amorphous Silicon (e.g., hydrogenated Amorphous Silicon), a hydrogenated amorphous Silicon Germanium alloy, Cadmium Telluride, a (Cd, Zn, Mg, Mn)Te compound, and p-type Cadmium Selenide. Second solar absorber layer **708** has a higher bandgap energy than solar absorber layer **206** such that second solar absorber layer **708** absorbs electromagnetic energy having shorter wavelengths than that absorbed by solar absorber layer **206**.

[0059] Second heterojunction partner layer **710** is formed on second solar absorber layer **708**. In an embodiment, second heterojunction partner layer **710** is formed of Cadmium Sulfide and second solar absorber layer **708** is formed of p-type Cadmium Selenide.

[0060] Top contact layer **712** is formed on second heterojunction partner layer **710**. A buffer layer (not shown in FIG. 7) is optionally disposed between second heterojunction partner layer **710** and top contact layer **712**. Top contact layer **712** and second heterojunction partner layer **710** are each at least partially transparent to wavelengths of electromagnetic energy **102** intended to be absorbed by second solar absorber layer **708** and solar absorber layer **206**.

[0061] FIG. 8 is a cross sectional view of one multi-junction photovoltaic cell **800**, which is an embodiment of photovoltaic cell **108**. Photovoltaic cell **800** is illustrated in FIG. 8 as including a second single-junction photovoltaic cell **826** formed on a first single-junction photovoltaic cell **824**. Accordingly, photovoltaic cell **800** is illustrated in FIG. 8 as being a two-junction or tandem photovoltaic cell. However, photovoltaic cell **800** may include more than two stacked single-junction photovoltaic cells and thereby have more than two junctions. For example, photovoltaic cell **800** could be a three-junction photovoltaic cell if a third single-junction photovoltaic cell were formed on a top surface **822** of photovoltaic cell **800**. Photovoltaic cell **800** may be considered to be a hybrid photovoltaic cell because at least two of its single junction photovoltaic cells (e.g., photovoltaic cells **824** and **826**) have different materials in their solar absorber layers.

[0062] First single-junction photovoltaic cell **824** includes a substrate **802**, a back contact layer **804**, a solar absorber layer **806**, a heterojunction partner layer **808**, an optional buffer layer **810**, and an optional interconnect layer **812**. Several photovoltaic cells **800** may be monolithically integrated onto substrate **802**. Substrate **802** forms a base and provides mechanical support for photovoltaic cell **800**. Examples of materials that may be used to form substrate **802** include polymers (e.g., polyimide), reinforced polymers, insulated metal foil (e.g., polymer coated metal foil), and glass. If substrate **802** is formed of a polymer or insulated metal foil, photovoltaic cell **800** may advantageously be flexible and lightweight compared to photovoltaic cells having a glass substrate. Additionally, forming substrate **802** of a polymer or insulated metal foil may advantageously allow photovoltaic cell **800** to support monolithic integration in contrast to photovoltaic cells having an uninsulated metal substrate. It should be noted, however, that substrate **802** could be formed of metal foil if photovoltaic cell **800** will not be used in monolithic integration applications.

[0063] Back contact layer **804** is formed on substrate **802**. Back contact layer **804** provides an electrical interface to photovoltaic cell **800**. Back contact layer **804** is formed of a material that is compatible with (e.g., forms a good contact with) solar absorber layer **806**; in an embodiment, back contact layer **804** includes molybdenum.

[0064] Solar absorber layer **806** is formed on back contact layer **804**; solar absorber layer **806** is formed of a material having a bulk p-type character and a photovoltaic effect such that solar absorber layer **806** is operable to at least partially absorb electromagnetic energy **102** and create corresponding electron-hole pairs. In particular, solar absorber layer **806** is formed of a Group IB-IIIB-VIB₂ material having bulk p-type character or its alloys. The Group IB-IIIB-VIB₂ material or its alloys may be a low bandgap material such that solar absorber layer **806** responds to relatively long wavelengths of electromagnetic energy (e.g., red and/or infrared light). Examples of materials that may be used to form solar absorber layer **806** include Copper Indium DiSelenide, Copper Indium DiTelluride, an alloy formed of Copper Indium DiSelenide and at least one of Gallium, Aluminum, and Sulfur, and an alloy formed of Copper Indium DiTelluride and at least one of Gallium, Aluminum, and Sulfur.

[0065] Heterojunction partner layer **808** is formed on solar absorber layer **806**. Heterojunction partner layer **808** may form a heterojunction with the material of solar absorber layer **806** having bulk p-type character. In an embodiment, Heterojunction partner layer **808** is formed of n-type material (e.g., Cadmium Sulfide). In another embodiment, heterojunction partner layer **808** is similar to heterojunction partner layer **208** of photovoltaic cell **200** of FIG. 2 in that heterojunction partner layer **808** is formed of a high resistivity material having the formula (Zn and/or Mg)(S, Se, O, and/or OH).

[0066] Photovoltaic cell **800** optionally includes buffer layer **810**; an exemplary material that may be used to form buffer layer **810** is undoped or high-resistivity ZnO. Conductive interconnect layer **812** is optionally formed on buffer layer **810**, if present, or on heterojunction partner layer **808** if buffer layer **810** is not present. Conductive interconnect layer **812** is required if heterojunction partner layer **808** is formed of a high resistivity material; however, if heterojunction partner layer **808** is formed of a conductive n-type material, interconnect layer **812** is not included in an embodiment of photovoltaic cell **800**. Interconnect layer **812** functions as an electrical and an optical interface between first photovoltaic cell **824** and second photovoltaic cell **826**. If interconnect layer **812** is not used, second photovoltaic cell **826** is formed directly on first photovoltaic cell **824**. Interconnect layer **812** may include a doped Zinc Oxide, undoped Zinc Oxide, Indium Tin Oxide, a doped Tin Oxide, undoped Tin Oxide, n-type amorphous Silicon, n-type amorphous Silicon Germanium, hydrogenated amorphous Silicon Carbide, and n-type microcrystalline Silicon. Interconnect layer **812** is at least partially transparent to electromagnetic energy intended to be absorbed by first photovoltaic cell **824**. In an embodiment of photovoltaic cell **800**, interconnect layer **812** serves to reflect some electromagnetic energy that passes through second photovoltaic cell **826** back into second photovoltaic cell **826** for absorption by it.

[0067] Second photovoltaic cell **826** includes layers **814**, **816**, and **818** of semiconductor material (e.g., amorphous Silicon) and an optional top contact layer **820**. In particular, a layer **814** of p-type semiconductor (e.g., p-type amorphous Silicon) is formed on interconnect layer **812** (if present), or on a top surface (e.g., surfaces **828** or **830**) of first photovoltaic cell **824** if interconnect layer **812** is not present. A layer **816** of intrinsic semiconductor (e.g., intrinsic amorphous Silicon) is formed on layer **814** of p-type semiconductor, and a layer **818** of n-type semiconductor (e.g., n-type amorphous Silicon) is

formed on the layer **816** of intrinsic semiconductor. In an embodiment, layers **814**, **816**, and **818** are formed of hydrogenated amorphous Silicon. In another embodiment, layers **814** and **818** are formed of hydrogenated amorphous Silicon, and layer **816** is formed of hydrogenated amorphous Silicon Germanium. Layers **814** and **818** may also be formed of microcrystalline Silicon in an embodiment. In another embodiment, layers **814** and **818** are each formed from one of hydrogenated amorphous Silicon Germanium, hydrogenated amorphous Silicon Carbide, and nanocrystalline Silicon. In embodiments of photovoltaic cell **800**, layer **816** has a graded composition or is formed of several discrete sublayers. Layer **816**, for example, is formed of a plurality of different materials, where each material has a different Silicon germanium alloy composition. As another example, layer **816** has a variable level of small crystalline domains of specified sizes to achieve specified bandgaps. As yet another example, layer **816** may be a graded bandgap layer of intrinsic amorphous Silicon germanium. Such designs of layers of intrinsic amorphous Silicon are discussed in the art (for example: X. Liao et al, Proc. 31st IEEE PVSC, 2005, and V. Suntharalingam et al, Proc. 1st WCPEC, 1994) and are used, for example, to reduce efficiency losses at interfaces to layer **816**.

[0068] Top contact layer **820** is optionally formed on layer **818** of n-type semiconductor. If one or more additional photovoltaic cells are formed on multi-junction photovoltaic cell **800**, top contact layer **820** need not be included. Top contact layer **820** is at least partially transparent to electromagnetic energy **102** in order to allow electromagnetic energy **102** to reach first and second photovoltaic cells **824** and **826**. Examples of materials that may be used to form top contact layer **820** include one of doped Zinc Oxide, Indium Tin Oxide, and doped Tin Oxide. A top surface **822** of top contact layer **820** may be roughened to increase light trapping of second photovoltaic cell **826**, thereby increasing its current generation and efficiency.

[0069] Embodiments of photovoltaic cell **800** advantageously have a relatively high efficiency despite being formed on a polyimide substrate. A polyimide substrate generally cannot support high processing temperatures required to fabricate a high efficiency photovoltaic cell. However, even if embodiments of photovoltaic cell **800** are fabricated at low temperatures, the multijunction structure of photovoltaic cell **800** may enable the embodiments to nevertheless obtain high efficiencies.

[0070] One embodiment of photovoltaic cell **800** has the following configuration: substrate **802** formed of glass, back contact layer **804** formed of molybdenum, solar absorber layer **806** formed of Copper Indium DiSelenide, heterojunction partner layer **808** formed of Zinc Oxide, buffer layer **810** formed of Zinc Oxide, interconnect layer **812** formed of doped Zinc Oxide, layer **814** formed of p-type amorphous Silicon, layer **816** formed of intrinsic amorphous Silicon, and layer **818** formed of n-type amorphous Silicon.

[0071] As has been previously discussed, a plurality of the photovoltaic cells of the present disclosure may be monolithically integrated onto a common substrate. For example, several photovoltaic cells **200**, **300**, **400**, **600**, **700**, or **800** may be monolithically integrated onto a common substrate. FIG. 9 is a cross sectional view of a plurality **900** of multi-junction photovoltaic cells **938** monolithically integrated onto a common substrate; such plurality of photovoltaic cells is an embodiment of module **100**. FIG. 9 illustrates plurality **900** including three multi-junction photovoltaic cells **938(1)**, **938**

(2), and **938(3)** (only parts of photovoltaic cells **938(1)** and **938(3)** are illustrated in FIG. 9); however, plurality **900** may include any number of photovoltaic cells **938** greater than 1. Each photovoltaic cell **938** includes N single-junction photovoltaic cells, where N is an integer that is greater than or equal to one. It should be noted that several photovoltaic cells **200**, **300**, **400**, **600**, **700**, or **800** may be monolithically integrated onto a common substrate in manners different from that illustrated in FIG. 9.

[0072] Bottom single junction photovoltaic cells **904** are formed on substrate **902**. Photovoltaic cells **904** include bottom contacts **910** (e.g., back contact layers formed of molybdenum) formed on substrate **902**. Junctions **912** are formed on bottom contacts **910**; junctions **912** each include, for example, a solar absorber layer and a heterojunction partner layer. Top contacts **914** are optionally formed on junctions **912**; top contacts **914** includes at least one of a conductive top contact layer (e.g., doped Zinc Oxide, undoped Zinc Oxide, Indium Tin Oxide, doped Tin Oxide, undoped Tin Oxide, n-type amorphous Silicon, n-type amorphous Silicon Germanium, hydrogenated amorphous Silicon Carbide, and n-type microcrystalline amorphous Silicon) and a buffer layer.

[0073] One or more intermediate layers of single-junction photovoltaic cells (represented by reference character **906**) are sequentially formed on bottom single-junction photovoltaic cells **904**. The individual layers of single-junction photovoltaic cells **906** are not shown in FIG. 9 in order to promote illustrative clarity. It should be noted that if plurality **900** includes only two single-junction photovoltaic cell layers (**904** and **908**), intermediate single-junction photovoltaic cell layers **906** will not be included in plurality **900**.

[0074] Top single junction photovoltaic cells **908** are formed on a top surface **936** of single junction photovoltaic cell layers **906** (or directly on bottom single-junction photovoltaic cells **904** if single junction photovoltaic cell layers **906** are not present). Similar to photovoltaic cells **904**, photovoltaic cells **908** include bottom contacts **916** formed on top surface **936**, junctions **918** formed on bottom contacts **916**, and top contacts **920** formed on junctions **918**. Junctions **918** may include, for example, N-I-P or P-I-N structures.

[0075] Scribes at least partially delineate each multi-junction photovoltaic cell **938**. For example, FIG. 9 illustrates photovoltaic cells **938(1)**, **938(2)**, and **938(3)** being at least partially defined by scribes. First isolation scribes **922** each extend from a top surface **928** of photovoltaic cells **908**, or from a top surface **940** of junctions **918** (if top contacts **920** are sufficiently conductive), to a top surface **930** of substrate **902**, or to a top surface of an insulator layer (not shown in FIG. 9) disposed on top surface **930**. First isolation scribes **922** are filled with an insulating material. Connecting scribes **924** each extend from top surface **928** of photovoltaic cells **908**, or from top surface **940** of junctions **918**, to a top surface **932** of bottom contacts **910**. Connecting scribes **924** are filled with a conductive material. If top contacts **920** are scribed, then the conductive material of each connecting scribe **924** extends over an adjacent first isolating scribe **922**; accordingly, each connecting scribe **924** electrically connects a section of top surface **928** of one photovoltaic cell **938** to a bottom contact of an adjacent photovoltaic cell **938**. Second isolating scribes **926** each extend from top surface **928** of photovoltaic cells **938** to a top surface **934** of a respective junction of a bottom single junction photovoltaic cell **904**, provided the solar absorber of the bottom single junction photovoltaic cell is sufficiently resistive, otherwise second

isolating scribe **926** may extend from top surface **928** to top surface **932** of bottom contacts **910**. Second isolating scribes **926** are illustrated as being filled with air in FIG. **9**, however, in other embodiments, isolating scribes **926** may be filled with another relatively non-conductive material.

P-Type Cadmium Selenide Absorber Layers

[0076] As deposited, Cadmium Selenide tends to be n-type. In many of the structures described herein, a p-type Cadmium Selenide layer is desired.

[0077] FIG. **10** shows one process **1000** of converting n-type Cadmium Selenide to p-type Cadmium Selenide. Process **1000** may enable use CdSe in structures and processes resembling those previously demonstrated in lower (1.5 electron volt) bandgap CdTe TFPV cells. Process **1000** also allows fabrication of a CdSe cell having a correct polarity for monolithic connection to an underlying p-type Cu(In, Ga, Al)(S, Se)₂ bottom cell. By a Cu(In, Ga, Al)(S, Se)₂, a material is meant that comprises Copper, at least one of Sulfur or Selenium, and at least one of Indium, Gallium, or Aluminum. For example, as discussed above, some embodiments of solar absorber layers **206** and **708** are formed of p-type CdSe, and process **1000** may be used to form such embodiments. As another example, process **1000** may be used to form the top CdSe solar absorber layers **1115** and **1216** of photovoltaic cells **1100** (FIG. **11**) and **1200** (FIG. **12**), respectively. Furthermore, process **1000** may be used to provide p-type CdSe for use in applications other than photovoltaic cell solar absorber layers.

[0078] Process **1000** begins with step **1002** where a layer of Cadmium Selenide is deposited. An example of step **1002** is sputtering a layer of Cadmium Selenide on a photovoltaic cell's back contact layer. Optional step **1004** is performed concurrently with step **1002**. In step **1004**, a dopant is deposited concurrently with the layer of Cadmium Selenide to form a doped Cadmium Selenide layer. Some commonly known potential p-type dopants that can be used for group IIB-VIB materials include, for example, at least one of a Group IA element, a Group IB element, and a Group VB element. However the effectiveness of these dopants in highly compensated group IIB-VIB materials such as CdSe, is tenuous at best, especially if subsequent high-temperature processing of the CdSe is desired to improve the properties of the CdSe and subsequent device efficiency. In an embodiment, Group IIIB and a Group VIIB elements are used in step **1004**. An example of step **1004** is depositing a Group IIIB elements, preferably lower cost elements such as Ga and Al, along with the layer of Cadmium Selenide.

[0079] In step **1006**, the layer of Cadmium Selenide (which may include a dopant deposited in optional step **1004**) is coated with a solution including a solvent (e.g., methanol) and at least one chloride selected from the group consisting of chlorides of Group IA elements, chlorides of Group IB elements, and chlorides of Group IIIB elements. Examples of such solution include a preferable GaCl₂ solution, a CuCl₂ solution, a mixed CuCl₂ and GaCl₂ solution, a mixed CuCl₂ and CdCl₂ solution, a mixed GaCl₂ and CdCl₂ solution, and a mixed CuCl₂, GaCl₂, CdCl₂ solution. An example of step **1006** is spin coating the layer of Cadmium Selenide with a solution of Gallium Chloride and methanol at a concentration of 0.1 to 0.00001 (preferably 0.001) Molar and allowing the coated layer to dry. As another example, the layer of Cad-

mium Selenide may be submersed in the solution and heated to 50 C-60 C for a period of 10 minutes to 20 minutes, then allowed to dry.

[0080] In step **1008**, the coated layer of Cadmium Selenide is heated in an environment having an ambient temperature of between 300 and 500 degrees Celsius (preferably 400 degrees Celsius) for a time between three and thirty minutes in a manner which minimizes loss (evaporation) of Selenium from the layer of Cadmium Selenide. For example, the Cadmium Selenide may be heated in a Selenium containing environment or a Selenium enriched atmosphere. As another example, the two layers of Cadmium Selenide may be disposed such that their surfaces are touching or nearly touching to physically impede evaporation of Selenium from the layers' surfaces. As yet another example, a non-porous cap may be placed on the coated layer of Cadmium Selenide during heating to physically impede the evaporation of Selenium from the Cadmium Selenide.

[0081] It should be noted that execution of optional step **1004** may advantageously allow additional freedom in selection of chlorides and chloride concentrations used in step **1006**. For example, if step **1004** is executed, step **1006** may be executed with the use of solely Cadmium Chloride as the chloride. Use of Cadmium Chloride may be advantageous because it may help to prevent erosion of Cadmium Selenide during the chloride treatment.

[0082] FIGS. **11** and **12** are cross sectional views of tandem photovoltaic cells **1100** and **1200**, respectively. Each of photovoltaic cells **1100** and **1200** are an embodiment of photovoltaic cell **108** of FIG. **1** and include a top solar absorber layer optimized for absorbing short wavelength "blue" photons, defined as those photons having wavelengths shorter than red light. The top solar absorber layers of photovoltaic cells **1100** and **1200** are formed of p-type Cadmium Selenide having a wide bandgap of 1.72 electron-volts. Embodiments of photovoltaic cells **1100** and **1200** advantageously have potential to reach high efficiencies, possibly above twenty percent, and high specific power (potentially greater than 2,000 watts per kilogram) when built on lightweight flexible substrates.

[0083] The CdSe junction is fabricated on top of a high-efficiency, but lower-bandgap, thin film photovoltaic junction ("TFPV") bottom junction having a photon absorber layer of a IB-IIIB-VIB₂ material such as a Copper-Indium-DiSelenide and related alloys with Gallium, Aluminum or Sulfur having the approximate formula Cu(In, Ga, or Al)(S, or Se)₂. As another example, the bottom junction may be formed of Copper Indium Gallium Selenide.

[0084] In photovoltaic cells **1100** and **1200**, the CdSe top cell absorbs light toward the blue end of the spectrum, transmitting unabsorbed light for absorption by the underlying Cu(In, Ga, Al)(S, Se)₂ cell. The CdSe layers of photovoltaic cells **1100** and **1200** are, for example, fabricated using an embodiment of process **1000**, FIG. **10**.

Structure of Photovoltaic Cell **1100**:

[0085] With reference to FIG. **11**, incident light **102** approaches the illuminated side of photovoltaic cell **1100**. Photovoltaic cell **1100** then has layers as follows.

[0086] Antireflective Coatings layer **1103** forms the top of photovoltaic cell **1100**. This layer, which may include several sublayers, serves to impedance-match incoming light **102** to underlying layers of photovoltaic cell **1100** to enhance efficiency by avoiding loss of incident photons to reflection.

Layer **1103** admits light to photovoltaic cell **1100**. Additional antireflective layers may also be used between other layers of photovoltaic cell **1100** having different indexes of refraction, such as between encapsulation/protection layer **1105** and transparent conductor layer **1107**.

[0087] Encapsulation/Protection layer **1105** is disposed below layer **1103**. Layer **1105** is a layer of a transparent material intended to provide mechanical and/or chemical protection to photovoltaic cell **1100**. Layer **1105** may include one or more polymers such as polyimides or silicones, or may include a sputter-deposited metal oxide layer or a transparent glass such as Silicon Dioxide.

[0088] Metal collection grid **1109** is disposed on transparent conductor layer **1107** as shown in FIG. **11**. This layer is optional. This layer or layers aid the lateral conduction to the cell terminals and is patterned so as to cover only a small percentage of the surface of photovoltaic cell **1100** while providing low resistance interconnection to transparent conductor layer **1107**. Collection grid **1109** collects electrical power from the transparent conductor layer **1107** and conducts it to terminals of photovoltaic cell **1100**. The collection grid **1109** and bottom collection or back contact layers **1125** may be patterned, and may contact each other at selected locations as known in the photovoltaic art, to electrically connect cells serially on the same substrate to obtain higher output voltages than those available from a single pair of junctions. Typical metal collection grids are multilayers, with the first layer being an adhesion and/or diffusion barrier layer, such as nickel or titanium, and another layer for conduction, such as aluminum or silver. Additional conductive layers may be used on top of the conduction layer, such as a layer of nickel.

[0089] A transparent conductor layer **1107** is disposed below encapsulation/protection layer **1105**. Conductor layer **1107** is, for example, a single layer of doped Tin Oxide, doped Zinc Oxide, or an Indium Tin Oxide compound. Conductor layer **1107** is thin, transparent, and conductive. It serves to carry current from the top cell to the metal collection grid **1109**. Optionally, a transparent buffer layer **1111** may be included. For example, conductor layer **1107** may be formed of relatively conductive material (e.g., Indium Tin Oxide) and buffer layer **1111** may be used and formed of a less conductive material, such as undoped Zinc Oxide.

[0090] An n-type heterojunction partner layer or window layer **1113** is disposed below conductor layer **1107** (or buffer layer **1111** if present). Heterojunction partner layer **1113** is, for example, Cadmium Sulfide (CdS). As another example, heterojunction partner layer **1113** may be formed of one of Indium Selenide, Zinc Selenide, Cadmium Zinc Selenide, Cadmium Selenide, Zinc Sulfide, Cadmium Oxide, Zinc Oxide, Zinc Magnesium Oxide, Tin Oxide, and Cadmium Zinc Sulfide. Heterojunction partner layer **1113** layer helps form the PN junction with the underlying CdSe layer **1115** which directs carriers generated by absorbed photons. Alternatively, heterojunction partner layer **1113** may be omitted if conductor layer **1107** is used in combination with a buffer layer **1111**, such as with buffer layer **1111** formed of undoped Zinc Oxide, undoped Zinc Magnesium Oxide, or undoped Tin Oxide.

[0091] A Cadmium Selenide (CdSe) layer **1115** is disposed below heterojunction partner layer **1113**. CdSe layer **1115** has been deposited as p-type, or converted to p-type, by post-treatment diffusion of a dopant, or by use of a process such as

process **1000** of FIG. **10**. P-type CdSe layer **1115** absorbs photons toward the blue end of the solar spectrum.

[0092] A transparent interconnect layer **1150** is disposed below CdSe layer **1115**. Interconnect layer **1150** may be a bilayer and therefore include two layers—back contact interface layer **1117** and conductor layer **1119**—as shown in FIG. **11**. Alternately, interconnect layer **1150** may be formed of a single layer. For example, interconnect layer **1150** may be formed of a single layer of one of doped Tin Oxide, doped Zinc Oxide, or Indium Tin Oxide. As another example, interconnect layer **1150** may include interface layer **1117** (e.g., formed of doped Zinc Telluride), and conductor layer **1119** formed of a conductive oxide. Interconnect layer **1150** serves as a back contact for the top photovoltaic junction.

[0093] An n-type second heterojunction partner layer **1121** is disposed below interconnect layer **1150**. Second heterojunction partner layer **1121** is, for example, one of Indium Selenide, Zinc Sulfide, Zinc Selenide, Cadmium Sulfide, Cadmium Zinc Sulfide, Zinc Oxide, or Zinc Magnesium Oxide. Second heterojunction partner layer **1121** helps to form a junction with layer **1123**.

[0094] A p-type solar absorber layer **1123** is disposed below second heterojunction interconnect layer **1121**. Solar absorber layer **1123** is formed of a group IB-IIIB-VIB₂ semiconductor such as Copper Indium DiSelenide, to form a low bandgap solar absorber, or a related alloy Cu(In, Ga, Al) (S, Se)₂ to optimize the bandgap and tandem device performance. In a particular embodiment, layer **1123** is CuInSe₂.

[0095] A metal back contact and current collection layer **1125** is disposed below solar absorber layer **1123**. Layer **1125** is, for example, formed of Molybdenum metal.

[0096] An optional layer **1127** of insulation may be disposed between back contact layer **1125** and substrate **1129**. Insulating layer **1127** is used, for example, when substrate **1129** is a conductive metal foil. Insulating layer **1127** is formed, for example, of an undoped oxide or a polymeric material such as a silicone or polyimide.

[0097] A substrate layer **1129** is disposed below back contact layer **1125** (or insulating layer **1127** if present). Substrate layer **1129** is, for example, metal foil, insulated metal foil, glass, or a heat-stable polymer such as polyimide or reinforced silicone.

[0098] One embodiment of photovoltaic cell **1100** has the following configuration: substrate **1129** formed of polyimide, no insulating layer **1127**, back contact layer **1125** formed of Molybdenum, solar absorber layer **1123** formed of Copper Indium DiSelenide, second heterojunction partner layer **1121** formed of Zinc Oxide, transparent conductor layer **1119** formed of Indium Tin Oxide, back contact interface layer **1117** formed of doped Zinc Telluride, solar absorber layer **1115** formed of p-type Cadmium Selenide, first heterojunction partner layer **1113** formed of Cadmium Sulfide, buffer layer **1111** formed of undoped Tin Oxide, transparent conductor layer **1107** formed of doped Tin Oxide, metallic grid **1109** formed of silver on a nickel adhesion layer, layer **1105** formed of Silicon Oxide, and antireflective coatings **1103** formed of Magnesium Fluoride.

Structure of Photovoltaic Cell **1200**:

[0099] In photovoltaic cell **1200** (FIG. **12**), a transparent substrate **1206** is used. Photovoltaic cell **1200** is an alternate embodiment of photovoltaic cell **1100** (FIG. **11**). In photovoltaic cell **1200**, incident light **102** enters through an antireflection coating layer **1204** into the substrate **1206**. Light then

passes through gaps in the optional collection grid metal **1210** and through transparent conductor layer **1208**. Transparent conductor layer **1208** may have a buffer layer **1212** as heretofore described with **1107** and **1111** of photovoltaic cell **1100** (FIG. 11).

[0100] Light passes from the transparent conductor layer **1208** (and buffer layer **1212** if present) and through a first heterojunction partner layer **1214** into the p-type CdSe absorber layer **1216** of the top junction. In layer **1216**, photons toward the blue end of the solar spectrum are absorbed, but photons toward the red end of the solar spectrum mostly pass through a back contact interface layer **1218** and a second transparent conductor layer **1220** into the bottom junction. (It should be noted that photovoltaic cell **1200** need not include both back contact interface layer **1218** and conductor layer **1220**. If both back contact interface layer **1218** and conductor layer **1220** are present, they may be collectively referred to as a bilayer.) The bottom junction has a heterojunction partner layer **1222** of Cadmium Sulfide, Zinc Sulfide, Cadmium Zinc Sulfide, Zinc Oxide, or Zinc Magnesium Oxide in contact with a low bandgap p-type group IB-IIIB-VIB₂ semiconductor layer **1224** such as the Cu(In, Ga, Al) (S, Se)₂ material previously discussed. The transmitted light is absorbed in this p-type layer **1224**.

[0101] A metallic back contact layer **1226**, preferably of molybdenum metal, serves as an electrical back contact to photovoltaic cell **1200**. Finally, a protective passivation coating or backing material **1228**, which need not be transparent, protects photovoltaic cell **1200**. The various layers are patterned as needed using a series of scribes or, alternatively photoetching, to expose the metallic grid layer **1210** and back contact layer **1226** for connection of leads to the device, to isolate particular areas of the device as individual cells, and to electrically connect individual cells in series to provide higher voltage output than attainable from a single tandem-junction pair.

[0102] One embodiment of photovoltaic cell **1200** has the following configuration: back contact layer **1226** formed of Molybdenum, solar absorber layer **1224** formed of Copper Indium DiSelenide, second heterojunction partner layer **1222** formed of Zinc Oxide, transparent conductor layer **1220** formed of Indium Tin Oxide, transparent back contact layer **1218** formed of p-type Zinc Telluride, solar absorber layer **1216** formed of Cadmium Selenide, first heterojunction partner layer **1214** formed of undoped Tin Oxide, buffer layer **1212** formed of undoped Tin Oxide, transparent conductor layer **1208** formed of doped Tin Oxide, no grid **1210**, substrate **1206** formed of glass, and antireflective coatings **1204** formed of Magnesium Fluoride.

Fabrication of Photovoltaic Cells **1100**:

[0103] Method **1300** of FIGS. 13 and 14 may be used to fabricate photovoltaic cell **1100** of FIG. 11. However, it should be noted that photovoltaic cell **1100** might be fabricated using a different method.

[0104] Method **1300** may make use conventional sputtering or of roll-to-roll sputter processing, as known in the art and described in U.S. Pat. No. 6,783,640, for deposition of most layers. A disclosure of a conventional sputtering process for thin-film photovoltaic devices using similar materials is contained in U.S. Pat. No. 5,393,675 to Compaan, which is hereby incorporated by reference. For this discussion, a flexible metal strip is assumed for substrate **1129**, although, as previously stated, other substrates are usable.

[0105] First, the metal substrate **1129** is coated **1302** with insulator layer **1127**. For the following deposition steps, the substrate is loaded into a suitable sputtering machine with a target chosen to give the desired composition of each layer, and deposition performed as known in the art.

[0106] While RF sputter deposition is preferred for most layers, as it can be used with a wide variety of materials, alternative thin-film deposition methods may be used for some layers. Alternative thin-film deposition methods that may be suitable for some layers include evaporation, printing, pulsed laser deposition, close-space sublimation, electrochemical deposition, chemical vapor deposition, wet chemical processing and molecular beam epitaxy.

[0107] Metal back contact layer **1125**, preferably Molybdenum, is deposited **1304**, following which the p-type Cu(In, Ga or Al) (S₂ or Se₂) low bandgap solar absorber layer **1123** is deposited preferably using a co-evaporation process **1306**. Solar absorber layer **1123** is then topped with a high-resistivity Zinc-Oxide partner layer **1121**, deposited **1308** preferably using chemical vapor deposition.

[0108] Next is sputter deposited **1310**, **1312** conductor layer **1119** and back contact interface layer **1117**, respectively. Conductor layer **1119** is, for example, Indium Tin Oxide. Back contact interface layer **1117** is preferably Cu doped ZnTe or is optionally nitrogen doped per the method described by Compaan et al, contained in U.S. Pat. No. 6,852,614, which is hereby incorporated herein by reference.

[0109] Next, a layer **1115** of Cadmium Selenide (CdSe) is deposited **1316**, preferably by sputtering, but alternatively this layer can be deposited via any of the known deposition techniques used for II-VI materials. Some common thin-film deposition techniques of II-VI materials include but are not limited to: RF sputtering, evaporation, printing, pulsed laser deposition, close-space sublimation, electro-chemical deposition, wet chemical processing, chemical vapor deposition, or molecular beam epitaxy.

[0110] The CdSe is then made p-type by a high-temperature chloride process that includes coating the CdSe with a solution including at least one chloride selected from the following: chlorides of Group IA elements, chlorides of Group IB elements, and chlorides of group IIIB elements. Examples of chlorides that may be used include, but are not limited to, Copper Chloride (CuCl₂), and/or Gallium Chloride (GaCl₂) with optional Cadmium Chloride (CdCl₂). The chloride coated CdSe is then heated, as discussed below, while at least partially preventing the evaporation of Selenium from the chloride coated CdSe.

[0111] For example, the CdSe may be made p-type as follows. Following the deposition **1316** of the doped or undoped CdSe layer, a wet GaCl₂ solution (with optional CuCl₂ and CdCl₂) is applied **1318** uniformly to the surface of the CdSe film. In one embodiment, the GaCl₂ is mixed in methanol (CH₃OH) at a concentration of 0.1 to 0.00001 (preferably 0.001) M. The solution is deposited on the CdSe surface via spin coating to uniformly distribute the solution across the CdSe surface. The volume of solution is preferably 0.04 ml per cm² of CdSe surface. Alternatively, the solution may be drop coat and knife "doctor" bladed across the CdSe surface. Alternatively, the solution may be sprayed or misted uniformly onto the CdSe surface. Alternatively, the chlorides may be deposited using a dry technique, such as chemical vapor deposition. Alternatively, the chlorides may be deposited from submersion in a heated chloride bath.

[0112] After applying **1318** the solution, the solution is allowed to dry on the CdSe surface, leaving the dried chloride on the surface. The CdSe and dried chloride are then placed into a chamber and heated **1320** in an environment having an ambient temperature in the range of 300 to 500° C., preferably 390 C for a time ranging from a three minutes to 30 minutes, preferably 20 minutes, with a strong selenium-containing background gas supplied immediately adjacent to the CdSe surface. The Selenium background gas helps prevent the evaporation of Selenium from the coated layer of CdSe. Alternately, instead of using a Selenium background, the evaporation of Selenium from the coated layer of CdSe may be physically impeded, such as by used of a non-porous cap on the CdSe layer, or by placing two or more layers of CdSe together or nearly touching. When a non-porous cap layer is used on the CdSe layer to impede evaporation of the selenium, this cap layer may be removed after the heating step, and need not remain as a permanent part of the photovoltaic cell.

[0113] In one embodiment, the selenium ambient may be provided via evaporation with the Se source in close proximity (within 12 inches) and directed at the CdSe surface. Alternatively, the Se is provided by passing the CdSe over a heated Se source plate for close-space sublimation of the Se to the CdSe surface in a background gas of air, Ar, O₂, or N₂. The concentrated Se ambient above the surface of the CdSe suppresses the loss of Selenium vapor from the surface during the high-temperature treatment. The high-temperature chloride treatment modifies the CdSe electronic and optical properties, making it suitable as a p-type solar absorber layer. Residual chloride is removed by washing **1321** with methanol.

[0114] Next, the heterojunction partner layer **1113** is deposited **1322**, preferably CdS by wet chemical processing on the now-p-type CdSe layer **1115**. In an alternative embodiment, the high-temperature treatment with CdCl₂, and/or CuCl₂ and/or GaCl₂ described previously, is performed after the deposition of this layer. In yet another alternate embodiment a second high-temperature treatment is performed using CdCl₂ only after the deposition of the CdS layer. In yet another alternative embodiment, no n-type heterojunction partner layer is used to form the junction—the heterojunction partner layer is replaced by an undoped oxide layer, buffer layer **1111** such as Tin Oxide, Zinc Oxide, or Zinc Magnesium Oxide, and the transparent conductor layer **1107**.

[0115] Following the heterojunction partner layer deposition, the optional undoped oxide buffer layer **1111**, such as Tin Oxide is deposited **1324** in some embodiments by sputtering.

[0116] Next, the photovoltaic cell **1100** is patterned. This may be performed by scribing as known in the art. Scribing may be performed by laser, mechanical scribing, roll print or photo etch with dry or wet etching, or other methods of selective removal of material from the photovoltaic device surface. A deep isolation scribing **1326** cuts a trench by selectively removing all layers above insulation layer **1127** in an isolation trench, and backfills the resulting trench with insulation **1131**, such as a non-conductive ink or oxide. A second contact scribing **1328** cuts a trench by selectively removing all layers above metal layer **1125**, with the resulting trench backfilled with a conductive material **1133**, such a conductive ink or oxide, which may be the next deposited conductor layer **1107**. The contact scribe thereby connects metal layer **1125** in

particular predetermined areas to transparent conductor layer **1107** to connect individual cells in series to obtain high voltage output.

[0117] Next, Indium Tin Oxide transparent conductor layer **1107** is deposited **1330**, preferably by sputtering.

[0118] An interconnect scribing **1332** is performed to remove at least the transparent conductor layer **1107** in a trench **1135** between individual cells. This trench **1135** may be left empty or backfilled with an insulator.

[0119] The metal collection grid **1109** is next deposited **1334**, if used, and patterned **1336** so it covers only a specific portion or pattern on the surface. This layer, when finished, occupies only a small percentage of the cell so as to admit light to the absorbing layers beneath it.

[0120] Next, encapsulation/protection layer **1105** and anti-reflective coating **1103** layer are deposited **1338**. Then, openings are etched **1340** in the encapsulation/protection and anti-reflective coating layers so that leads may be attached **1342** and the device is cut into finished devices.

Fabrication of Photovoltaic Cells **1200**:

[0121] FIGS. **15-16** illustrate a method **1500** fabricating photovoltaic cell **1200** of FIG. **12**. Method **1500** is an embodiment of method **1300** of FIGS. **13-14**. It should be noted that photovoltaic cell **1200** may be fabricated using methods other than method **1500**.

[0122] Method **1500** begins with deposition **1502** and patterning of the optional collection grid **1210** on a transparent substrate **1206**. Following patterning of this layer, a transparent conductor layer **1208** is deposited **1504**, preferably Indium Tin Oxide but alternatively transparent conductors such as doped Tin Oxide (SnO₂), and doped Zinc Oxide (ZnO) may be used. Conductor layer **1208** is deposited by sputter deposition and is thin, transparent, and conductive. It serves to carry current from the top cell to the metal collection grid **1210**. Optionally, buffer layer **1212** may be sputtered **1506**. Buffer layer **1212** is, for example, undoped Zinc Oxide or undoped Tin Oxide.

[0123] Next, a heterojunction partner layer **1214**, preferably of CdS, is deposited **1508**, preferably by wet chemical processing although other deposition methods known in the art such as sputtering may be used. Following this, a layer of CdSe **1216** is deposited, preferably by sputtering **1510**.

[0124] The CdSe is then made p-type by a high-temperature chloride process that includes coating CdSe layer **1216** with a solution including at least one chloride selected from the following chlorides: chlorides of Group IA elements, chlorides of Group IB elements, and chlorides of Group IIIB elements. Examples of solutions that may be used to coat CdSe layer **1216** include, but are not limited to, Copper Chloride (CuCl₂), and/or Gallium Chloride (GaCl₂) with optional Cadmium Chloride (CdCl₂). The coated CdSe layer **1216** is subsequently heated while at least partially preventing the evaporation of Selenium from the coated CdSe layer **1216**. For example, the coated CdSe layer may be heated in a Selenium environment.

[0125] The following is one example of how CdSe layer **1216** may be made p-type. Following the deposition **1510** of the doped or undoped CdSe layer, a wet GaCl₂ solution (with optional CuCl₂ and CdCl₂) is applied **1512** uniformly to the surface of the CdSe film. In one embodiment, the GaCl₂ is mixed in methanol (CH₃OH) at a concentration of 0.1 to 0.00001 (preferably 0.001) Molar. The solution is deposited on the CdSe surface via spin coating to uniformly distribute

the solution across the CdSe surface. The volume of solution is preferably 0.04 ml per cm² of CdSe surface. Alternatively the solution may be drop coat and knife “doctor” bladed across the CdSe surface. Alternatively, the solution may be sprayed or misted uniformly onto the CdSe surface. Alternatively, the chloride is applied by chemical vapor deposition (CVD). Alternatively, the chlorides may be deposited from submersion in a heated chloride bath.

[0126] After applying **1512** the solution, the solution is allowed to dry on the CdSe surface, leaving the chloride on the surface. The device, including the CdSe film coated with dried chloride, is then placed into a chamber and heated **1514** in an environment having an ambient temperature ranging from 300 to 500° C., preferably 390 C for a time ranging from a three minutes to 30 minutes, preferably 20 minutes, with a strong Selenium containing background gas environment supplied immediately adjacent to the CdSe surface to prevent evaporation of Selenium from the CdSe surface. As an alternative to providing a CdSe environment, evaporation of Selenium from the CdSe surface may be physically impeded, such as by placing two or more layers of CdSe such that their surfaces touch, or nearly touch, or by placing a non-porous cap on the CdSe layer. In one embodiment, the Selenium ambient may be provided via evaporation with the Se source in close proximity (within 12 inches) and directed at the CdSe surface. Alternatively, the Se is provided by passing the CdSe over a heated Se source plate for close-space sublimation of the Se to the CdSe surface in a background gas of air, Ar, O₂, or N₂. The concentrated Se ambient above the surface of the CdSe suppresses evaporative loss of Se from the surface during the high-temperature treatment. The high-temperature chloride treatment modifies the CdSe electronic and optical properties, making it suitable as a p-type solar absorber layer. Residual chloride is removed by washing **1516** with methanol.

[0127] Next is sputter deposited **1518** a transparent conductor interface layer **1218**. This is ZnTe with optional Cu doping or with optional nitrogen doping per the method described by Compaan et al, contained in U.S. Pat. No. 6,852,614. Next, a conductive back contact layer **1220**, preferably a doped Tin Oxide or an Indium Tin oxide layer, is deposited **1520**.

[0128] Next, the red-optimized photovoltaic junction is formed. To do this, processing continues with deposition **1522** of a high-resistivity Zinc-Oxide heterojunction partner layer **1222** is deposited by sputtering, or chemical vapor deposition. Then, the p-type Cu(In, Ga or Al) (S₂ or Se₂) low bandgap solar absorber layer **1224** is deposited, preferably using co-evaporation **1524**.

[0129] Next, some patterning steps are performed to separate the device into several separate photovoltaic cells that can be strung together in series to obtain higher voltage output than available with a single hybrid stack. A first isolation scribeline **1526** cuts through all layers (excluding substrate **1206** and antireflective coatings **1204**) and is backfilled with insulator, such as a non-conductive ink or oxide. A second contact scribeline **1528** cuts through all layers above (excluding substrate **1206** and antireflective coatings **1204**), but stops at transparent conductor layer **1208** so as to permit contact to be made to, either the transparent conductor layer **1208** or the collection grid layer **1210**.

[0130] Back contact metal layer **1226** is then deposited **1530**. A third isolation scribeline **1532** is performed that cuts through back contact **1226** but stops above transparent conductor layer **1208** or collection grid layer **1210**. The cell is

then finished by depositing **1534** protection layers **1228**, with openings in this layer for lead attachment; and depositing **1536** an antireflective coating **1204** on the opposite, illuminated, side of the substrate **1206**.

[0131] For purposes of this document, the term blue includes wavelengths that are shorter than those of red light, including some red light but predominately yellow through the blue end of the spectrum, including ultraviolet light, but may also contain some absorption of the entire visible spectrum. Similarly, the term red includes wavelengths that are predominately near the red end of the spectrum including infrared. While the top, blue-optimized, cell of photovoltaic cells **1100** and **1200** is largely transparent to red and infrared light, it may absorb small amounts of red and infrared light because of defects and impurities. The bottom, red-optimized, cell may also absorb some short wavelength light, including blue light, that escapes absorption in the top cell.

[0132] Similarly, when a layer is described as transparent, it need transmit a majority of light incident at appropriate angles; it may absorb, scatter, and reflect small amounts of light.

[0133] Changes may be made in the above methods and systems without departing from the scope hereof. It should thus be noted that the matter contained in the above description or shown in the accompanying drawings should be interpreted as illustrative and not in a limiting sense. The following claims are intended to cover generic and specific features described herein, as well as all statements of the scope of the present method and system, which, as a matter of language, might be said to fall therebetween.

What is claimed is:

1. A photovoltaic cell, comprising:
 - a transparent conductor layer;
 - a first heterojunction partner layer;
 - a p-type Cadmium Selenide layer in contact with the first heterojunction partner layer; and
 - a first electrical contact layer.
2. The photovoltaic cell of claim 1, wherein the first heterojunction partner layer comprises a material selected from the group consisting of Zinc Selenide, Cadmium Sulfide, Cadmium Zinc Selenide, Cadmium Selenide, Zinc Sulfide, Cadmium Oxide, Zinc Oxide, Zinc Magnesium Oxide, Tin Oxide, and Cadmium Zinc Sulfide.
3. The photovoltaic cell of claim 1, further comprising a buffer layer, between the transparent conductor layer and the first heterojunction partner layer.
4. The photovoltaic cell of claim 3, wherein the buffer layer is formed of a material selected from the group consisting of undoped Zinc Oxide, Zinc Magnesium Oxide, and Tin Oxide.
5. The photovoltaic cell of claim 1, wherein the first electrical contact layer is a first back contact layer.
6. The photovoltaic cell of claim 1, wherein the first electrical contact layer is a bilayer.
7. The photovoltaic cell of claim 6 wherein the first electrical contact layer contains a layer of doped ZnTe and a layer of a material selected from the group consisting of a metal, and a transparent conducting oxide.
8. The photovoltaic cell of claim 1, wherein the first electrical contact layer comprises a second transparent conductor layer, and further comprising:
 - a second heterojunction partner layer,
 - a IB-IIIB-VIB₂ semiconductor layer, and
 - a second back contact layer.

9. The photovoltaic cell of claim 8 wherein the IB-IIIB-VIB₂ semiconductor layer comprises a layer of Copper-Indium-Diselenide (CIS).

10. The photovoltaic cell of claim 8, wherein the first heterojunction partner layer comprises a material selected from the group consisting of Zinc Selenide, Cadmium Sulfide, Cadmium Zinc Selenide, Cadmium Selenide, Zinc Sulfide, Cadmium Oxide, Zinc Oxide, Zinc Magnesium Oxide, Tin Oxide, and Cadmium Zinc Sulfide.

11. The photovoltaic cell of claim 8, further comprising a buffer layer, between the transparent conductor layer and the first heterojunction partner layer.

12. The photovoltaic cell of claim 11, wherein the buffer layer is formed of a material selected from the group consisting of undoped Zinc Oxide, Zinc Magnesium Oxide, and Tin Oxide.

13. The photovoltaic cell of claim 8 wherein the IB-IIIB-VIB₂ semiconductor layer is selected from the group of materials having the approximate formula Cu(In, Ga, or Al) (S, or Se)₂.

14. The photovoltaic cell of claim 8, wherein the first electrical contact layer comprises a bilayer.

15. The photovoltaic cell of claim 14, wherein the bilayer comprises a layer of doped ZnTe and a layer of a material selected from the group consisting of a metal and a conductive oxide.

16. The photovoltaic cell of claim 1, wherein the p-type Cadmium Selenide layer is made by a process comprising:
depositing a layer of Cadmium Selenide;

coating the layer of Cadmium Selenide with a solution comprising at least one of chloride selected from the group consisting of chlorides of Group IA elements, chlorides of group IB elements, and chlorides of Group IIIB elements; and

heat-treating the layer of Cadmium Selenide while at least partially preventing evaporation of Selenium from the layer of Cadmium Selenide.

17. The photovoltaic cell of claim 16, wherein Selenium is at least partially prevented from evaporating from the layer of Cadmium Selenide during the step of heat-treating by executing the step of heat-treating in a Selenium enriched atmosphere.

18. The photovoltaic cell of claim 16, wherein Selenium is at least partially prevented from evaporating from the layer of Cadmium Selenide during the step of heat-treating by physically impeding the flow of Selenium vapor from the layer of Cadmium Selenide.

19. The photovoltaic cell of claim 16, the solution further comprising Cadmium Chloride.

20. A hybrid multi-junction photovoltaic cell, comprising:
a polymer substrate for providing mechanical support for the photovoltaic cell;

a back contact layer formed on the substrate;

a bottom solar absorber layer formed on the back contact layer, the bottom solar absorber layer including a material selected from the group consisting of a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character, and an alloy of a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character;

a heterojunction partner layer formed on the bottom solar absorber layer;

a layer of p-type semiconductor formed above the heterojunction partner layer;

a layer of intrinsic semiconductor formed on the layer of p-type semiconductor; and

a layer of n-type semiconductor formed on the layer of intrinsic semiconductor.

21. The photovoltaic cell of claim 20, the polymer substrate being formed of polyimide.

22. The photovoltaic cell of claim 20, the bottom solar absorber layer comprising a material selected from the group consisting of Copper Indium DiSelenide, Copper Indium DiTelluride, and an alloy formed of Copper Indium DiSelenide and at least one of Gallium, Aluminum, Tellurium and Sulfur.

23. The photovoltaic cell of claim 20, the heterojunction partner layer comprising an n-type material.

24. The photovoltaic cell of claim 20, the heterojunction partner layer comprising at least one layer of a high resistivity material having a resistivity of at least 100 ohms-centimeter, the high resistivity material being a material having the formula (Zn and/or Mg)(S, Se, O, and/or OH).

25. The photovoltaic cell of claim 24, wherein the at least one layer of high resistivity material of the heterojunction partner layer has a resistivity of at least 1,000 ohms-centimeter.

26. The photovoltaic cell of claim 24, the heterojunction partner layer being formed using a chemical vapor deposition process.

27. The photovoltaic cell of claim 20, further comprising an interconnect layer disposed between the heterojunction partner layer and the layer of p-type semiconductor.

28. The photovoltaic cell of claim 27, the interconnect layer comprising a material selected from the group consisting of doped Zinc Oxide, undoped Zinc Oxide, Indium Tin Oxide, doped Tin Oxide, undoped Tin Oxide, n-type amorphous Silicon, n-type amorphous Silicon Germanium, hydrogenated amorphous Silicon Carbide, and n-type microcrystalline Silicon.

29. The photovoltaic cell of claim 20, the back contact layer comprising Molybdenum.

30. The photovoltaic cell of claim 20, the layer of p-type semiconductor and the layer of n-type semiconductor each being formed from a material selected from the group consisting of hydrogenated amorphous Silicon, hydrogenated amorphous Silicon Germanium, hydrogenated amorphous Silicon Carbide, nanocrystalline Silicon, and microcrystalline Silicon.

31. The photovoltaic cell of claim 20, the layer of intrinsic semiconductor being formed of hydrogenated amorphous Silicon Germanium.

32. The photovoltaic cell of claim 20, further comprising at least one additional single junction photovoltaic cell formed above the layer of n-type semiconductor.

33. A module of a plurality of hybrid multi-junction photovoltaic cells, comprising:

a substrate for providing mechanical support for the photovoltaic cells;

a back contact layer formed on the substrate;

a bottom solar absorber layer formed on the back contact layer, the bottom solar absorber layer including a material selected from the group consisting of a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character, and an alloy of a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character;

an n-type heterojunction partner layer formed on the bottom solar absorber layer;

a contact layer of p-type semiconductor formed above the heterojunction partner layer;

a primary solar absorber layer formed on the contact layer of p-type semiconductor, the primary solar absorber layer formed of a material selected from the group consisting of an intrinsic semiconductor and a p-type semiconductor;

a layer of n-type semiconductor formed on the primary solar absorber layer;

a top contact layer formed on the layer of n-type semiconductor;

at least one first isolating scribe extending at least from a top surface of the layer of n-type semiconductor to a top surface of the substrate, the first isolating scribe being filled with an insulating material;

at least one connecting scribe extending at least from the top surface of the layer of n-type semiconductor to a top surface of the back contact layer, the connecting scribe being filled with a conductive material; and

at least one second isolating scribe extending at least from a top surface of the top contact layer to a top surface of the bottom solar absorber layer.

34. The module of claim **33**, the heterojunction partner layer being formed of at least one layer of a high resistivity material having a resistivity of at least 100 ohms-centimeter, the high resistivity material being a material having the formula (Zn and/or Mg)(S, Se, O, and/or OH).

35. The module of claim **34**, wherein the heterojunction partner layer is formed using a chemical vapor deposition process.

36. The module of claim **34**, wherein the at least one layer of high resistivity material of the heterojunction partner layer has a resistivity of at least 1,000 ohms-centimeter.

37. The module of claim **33**, further comprising a conductive interconnect layer disposed between the heterojunction partner layer and the contact layer of p-type semiconductor, the conductive interconnect layer comprising a material selected from the group consisting of doped Zinc Oxide, Indium Tin Oxide, doped Tin Oxide, n-type amorphous Silicon, n-type amorphous Silicon Germanium, n-type hydrogenated amorphous Silicon Carbide, and n-type microcrystalline Silicon.

38. The module of claim **33**, the contact layer of p-type semiconductor and the layer of n-type semiconductor each being formed from a material selected from the group consisting of hydrogenated amorphous Silicon, hydrogenated amorphous Silicon Germanium, hydrogenated amorphous Silicon Carbide, nanocrystalline Silicon, and microcrystalline Silicon, and the primary solar absorber layer being formed of hydrogenated amorphous Silicon Germanium.

39. The module of claim **33**, the contact layer of p-type semiconductor being doped ZnTe, and the primary solar absorber layer being p-type CdSe.

40. The module of claim **33**, further comprising at least one additional single junction photovoltaic cell disposed between the heterojunction partner layer and the contact layer of p-type semiconductor.

41. A multi-junction photovoltaic cell, comprising:

a substrate for providing mechanical support for the photovoltaic cell;

a back contact layer formed on the substrate;

a solar absorber layer formed on the back contact layer, the solar absorber layer being formed of a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character;

a heterojunction partner layer formed on the solar absorber layer, the heterojunction partner layer comprising at least one layer of a high resistivity material having a resistivity of at least 100 ohms-centimeter, the high resistivity material being a material having the formula (Zn and/or Mg)(S, Se, O, and/or OH);

a conductive interconnect layer formed above the heterojunction partner layer; and

at least one additional single-junction photovoltaic cell formed on the conductive interconnect layer.

42. The photovoltaic cell of claim **41**, wherein the at least one layer of high resistivity material of the heterojunction partner layer has a resistivity of at least 1,000 ohms-centimeter.

43. The photovoltaic cell of claim **41**, the heterojunction partner layer being formed using a chemical vapor deposition process.

44. The photovoltaic cell of claim **41**, the substrate being formed from a material selected from the group consisting of a polymer, a reinforced polymer, polyimide, a metal foil, an insulated metal foil, and glass.

45. The photovoltaic cell of claim **41**, the low bandgap Group IB-IIIB-VIB₂ material being selected from the group consisting of Copper Indium DiSelenide, Copper Indium DiTelluride, an alloy formed of Copper Indium DiSelenide and at least one of Gallium, Aluminum, Tellurium and Sulfur, and an alloy formed of Copper Indium DiTelluride and at least one of Gallium, Aluminum, Selenium and Sulfur.

46. The photovoltaic cell of claim **41**, further comprising a buffer layer disposed between the heterojunction partner layer and the conductive interconnect layer.

47. The photovoltaic cell of claim **41**, the additional single-junction photovoltaic cell comprising a solar absorber layer formed of a material selected from the group consisting of a Cu(In, Ga, Al)Se₂ compound, a Cu(In, Ga, Al)S₂ compound, hydrogenated amorphous Silicon, hydrogenated amorphous Silicon Germanium alloy, a (Cd, Zn, Mg, Mn)Te compound, and Cadmium Selenide.

48. The photovoltaic cell of claim **41**, the additional single-junction photovoltaic cell comprising a solar absorber layer formed of p-type Cadmium Selenide.

49. A method of making a p-type Cadmium Selenide semiconductor material, comprising:

depositing a layer of Cadmium Selenide;

coating the layer of Cadmium Selenide with a solution comprising a solvent and at least one of chloride selected from the group consisting of chlorides of Group IA elements, chlorides of group IB elements, and chlorides of Group IIIB elements; and

heating the layer of Cadmium Selenide in an environment having an ambient temperature of between 300 and 500 degrees Celsius for a time between three and thirty minutes while at least partially preventing the evaporation of Selenium from the layer of Cadmium Selenide.

50. The method of claim **49**, wherein Selenium is at least partially prevented from evaporating from the layer of Cadmium Selenide during the step of heating by executing the step of heating in a Selenium enriched atmosphere.

51. The method of claim **49**, wherein Selenium is at least partially prevented from evaporating from the layer of Cad-

mium Selenide during the step of heating by physically impeding the evaporation of Selenium from the layer of Cadmium Selenide.

52. The method of claim **49**, wherein the solution comprises Copper Chloride and a solvent.

53. The method of claim **49**, wherein the solution comprises Gallium Chloride and a solvent.

54. The method of claim **49**, wherein the solution comprises Copper Chloride, Gallium Chloride, and a solvent.

55. The method of claim **49**, wherein the solution further comprises Cadmium Chloride.

56. A method of making a photovoltaic device, comprising:
depositing a contact layer;

depositing a layer of Cadmium Selenide;

coating the layer of Cadmium Selenide with a solution comprising a solvent and at least one of chloride selected from the group consisting of chlorides of Group IA elements, chlorides of group IB elements, and chlorides of Group IIIB elements;

heating the layer of Cadmium Selenide in an environment having an ambient temperature of between 300 and 500 degrees Celsius for a time between three and thirty minutes while at least partially preventing the evaporation of Selenium from the layer of Cadmium Selenide;

depositing a heterojunction partner layer; and

depositing a transparent conductor layer.

57. The method of claim **56**, wherein Selenium is at least partially prevented from evaporating from the layer of Cadmium Selenide during the step of heating by executing the step of heating in a Selenium enriched atmosphere.

58. The method of claim **56**, wherein Selenium is at least partially prevented from evaporating from the layer of Cadmium Selenide during the step of heating by physically impeding the evaporation of Selenium from the layer of Cadmium Selenide.

59. The method of claim **56**, wherein the solution comprises Copper Chloride and a solvent.

60. The method of claim **56**, wherein the solution comprises Gallium Chloride and a solvent.

61. The method of claim **56**, wherein the solution comprises Copper Chloride, Gallium Chloride, and a solvent.

62. The method of claim **56**, wherein the solution further comprises Cadmium Chloride.

63. The method of claim **56**, wherein the heterojunction partner layer is a material selected from the group consisting of Zinc Selenide, Cadmium Sulfide, Cadmium Zinc Selenide, Cadmium Selenide, Zinc Sulfide, Cadmium Oxide, Zinc Oxide, Zinc Magnesium Oxide, Tin Oxide, and Cadmium Zinc Sulfide.

64. The method of claim **56**, further comprising depositing an undoped buffer layer between the heterojunction partner layer and the transparent conductor layer.

65. The method of claim **56**, wherein the contact layer is a bilayer.

66. The method of claim **65**, wherein the contact layer comprises a layer of doped ZnTe and a layer of a material selected from the group consisting of a metal, and a transparent conducting oxide.

67. A method of making a photovoltaic device, comprising:
depositing a transparent conductor layer;

depositing a heterojunction partner layer;

depositing a layer of Cadmium Selenide;

coating the layer of Cadmium Selenide with a solution comprising a solvent and at least one of chloride selected

from the group consisting of chlorides of Group IA elements, chlorides of group IB elements, and chlorides of Group IIIB elements;

heating the layer of Cadmium Selenide in an environment having an ambient temperature of between 300 and 500 degrees Celsius for a time between three and thirty minutes while at least partially preventing the evaporation of Selenium from the layer of Cadmium Selenide; and

depositing a contact layer.

68. The method of claim **67**, wherein Selenium is at least partially prevented from evaporating from the layer of Cadmium Selenide during the step of heating by executing the step of heating in a Selenium enriched atmosphere.

69. The method of claim **67**, wherein Selenium is at least partially prevented from evaporating from the layer of Cadmium Selenide during the step of heating by physically impeding the evaporation of Selenium from the layer of Cadmium Selenide.

70. The method of claim **67**, wherein the solution comprises Copper Chloride and a solvent.

71. The method of claim **67**, wherein the solution comprises Gallium Chloride and a solvent.

72. The method of claim **67**, wherein the solution comprises Copper Chloride, Gallium Chloride, and a solvent.

73. The method of claim **67**, wherein the solution further comprises Chloride.

74. The method of claim **67**, wherein the heterojunction partner layer is a layer of a material selected from the group consisting of Zinc Selenide, Cadmium Sulfide, Cadmium Zinc Selenide, Cadmium Selenide, Zinc Sulfide, Cadmium Oxide, Zinc Oxide, Zinc Magnesium Oxide, Tin Oxide, and Cadmium Zinc Sulfide.

75. The method of claim **67**, further comprising depositing an undoped buffer layer between the transparent conductor layer and the heterojunction partner layer.

76. The method of claim **67**, wherein the contact layer is a bilayer.

77. The method of claim **76**, wherein the contact layer comprises a layer of doped ZnTe and a layer of a material selected from the group consisting of a metal layer, and a transparent conducting oxide layer.

78. A process for forming a hybrid multi-junction photovoltaic cell, comprising:

forming a first single-junction photovoltaic cell on a substrate, including the steps of:

forming a first back contact layer on the substrate,

forming a first solar absorber layer on the back contact layer, the first solar absorber layer being formed of a low bandgap Group IB-IIIB-VIB₂ material having bulk p-type character,

forming a first heterojunction partner layer on the first solar absorber layer, the first heterojunction partner layer comprising at least one layer of a high resistivity material having a resistivity of at least 100 ohm-centimeter, the high resistivity material being a material having the formula (Zn and/or Mg)(S, Se, O, and/or OH);

forming a conductive interconnect layer above the first heterojunction partner layer of the first single-junction photovoltaic cell; and

forming at least one additional single-junction photovoltaic cell above the conductive interconnect layer.

79. The process of claim **78**, wherein the at least one layer of high resistivity material of the heterojunction partner layer has a resistivity of at least 1,000 ohms-centimeter.

80. The process of claim **78**, the low bandgap Group IB-IIIB-VIB₂ material being selected from the group consisting of Copper Indium DiSelenide, Copper Indium DiTelluride, an alloy formed of Copper Indium DiSelenide and at least one of Gallium, Aluminum, Tellurium and Sulfur.

81. The process of claim **78**, the step of forming the first heterojunction partner layer including one of performing a chemical vapor deposition process, a wet chemical bath deposition process, and a low energy sputtering process.

82. The process of claim **81**, the first heterojunction partner layer being formed using a chemical vapor deposition process.

83. The process of claim **78**, the step of forming the first solar absorber layer including performing at least of one a selenization process, a sulfurization process, a tellurization

process, a thermal evaporation process, an electron beam evaporation process, a sputtering process, an electrodeposition process, a molecular beam epitaxy process, and a chemical vapor deposition process.

84. The process of claim **78**, the step of forming at least one additional single-junction photovoltaic cell comprising:

forming a second back contact layer on the conductive interconnect layer, and

forming a second solar absorber layer on the second back contact layer, the second solar absorber layer having a higher bandgap energy than the first solar absorber layer.

85. The process of claim **84**, the second solar absorber layer being formed of a material selected from the group consisting of a Cu(In, Ga, Al)Se₂ compound, a Cu(In, Ga, Al)S₂ compound, hydrogenated amorphous Silicon, hydrogenated amorphous Silicon Germanium alloy, a (Cd, Zn, Mg, Mn)Te compound, and Cadmium Selenide.

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